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Leem et al.

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(54) **ORGANIC PHOTOELECTRONIC DEVICE AND IMAGE SENSOR**

(58) **Field of Classification Search**

CPC C08G 61/123; H01L 27/307; H01L 51/44; H01L 2251/303; H01L 51/0046;

(Continued)

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Seon-Jeong Lim, Yongin-si (KR); **Yong Wan Jin**, Seoul (KR)

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(*) Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 757 days.

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(21) Appl. No.: **15/471,289**

Primary Examiner — Jay C Kim

(22) Filed: **Mar. 28, 2017**

(74) *Attorney, Agent, or Firm* — Harness, Dickey & Pierce, P.L.C.

(65) **Prior Publication Data**

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(57) **ABSTRACT**

(30) **Foreign Application Priority Data**

Jun. 29, 2016 (KR) 10-2016-0081554

An organic photoelectronic device includes a first electrode and a second electrode facing each other and a light-absorption layer between the first electrode and the second electrode and including a photoelectric conversion region including a p-type light-absorbing material and an n-type light-absorbing material and a doped region including an exciton quencher and at least one of the p-type light-absorbing material and the n-type light-absorbing material, wherein at least one of the p-type light-absorbing material and the n-type light-absorbing material selectively absorbs a part of visible light, and an image sensor includes the same.

20 Claims, 14 Drawing Sheets

(51) **Int. Cl.**

H01L 47/00 (2006.01)
H01L 27/30 (2006.01)

(Continued)

(52) **U.S. Cl.**

CPC **H01L 27/307** (2013.01); **H01L 51/002** (2013.01); **H01L 51/0064** (2013.01);

(Continued)



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STIC STN Chemical structure search results for Formula 1 (Year: 2021).

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FIG. 1

100

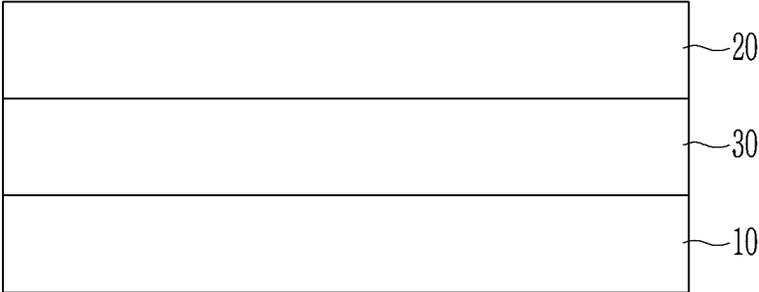


FIG. 2

100

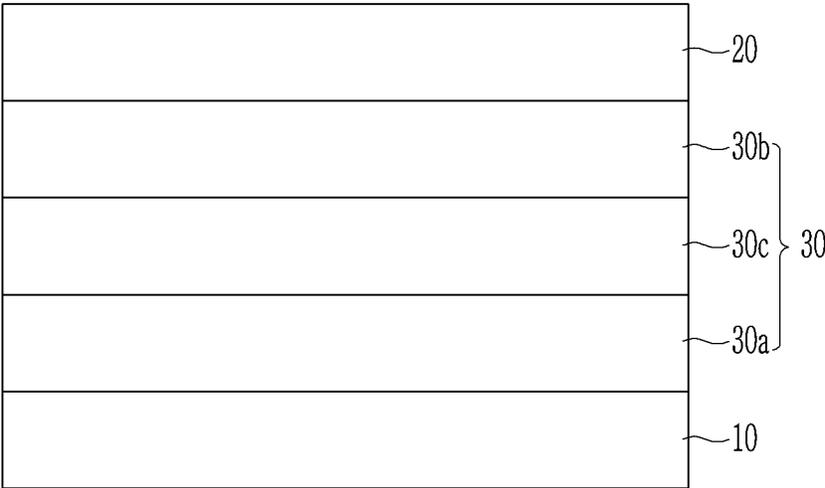


FIG. 3

200

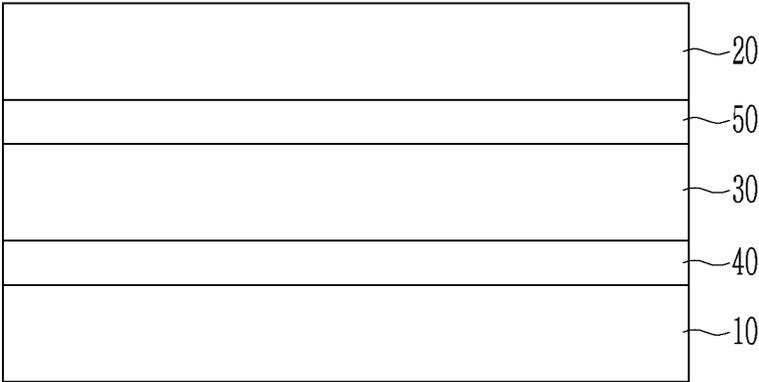


FIG. 4

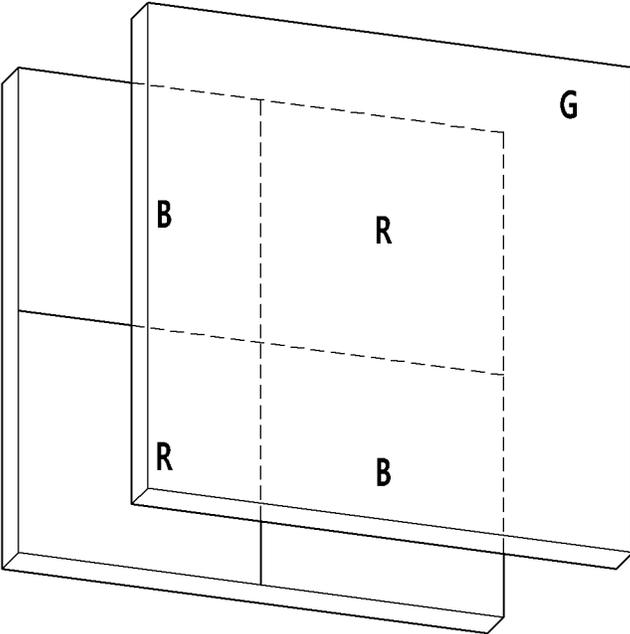


FIG. 5A

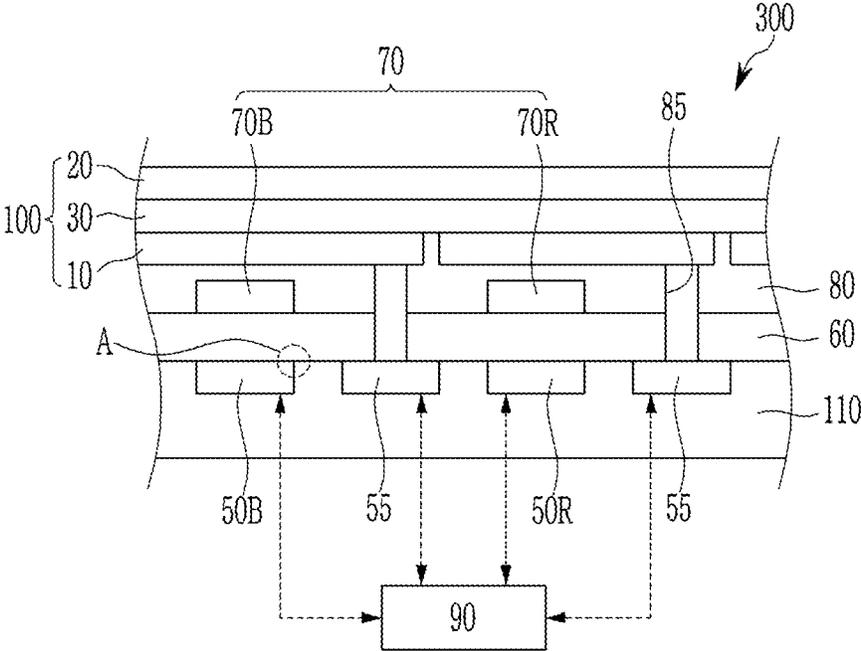


FIG. 5B

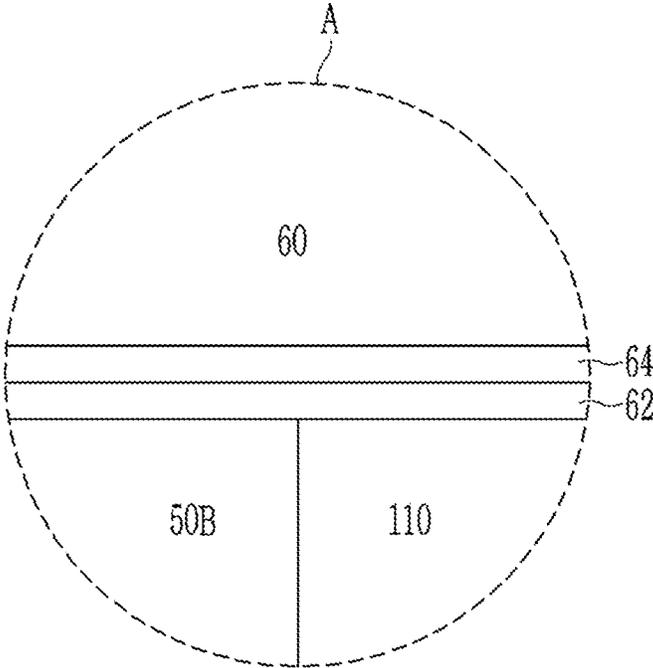


FIG. 6

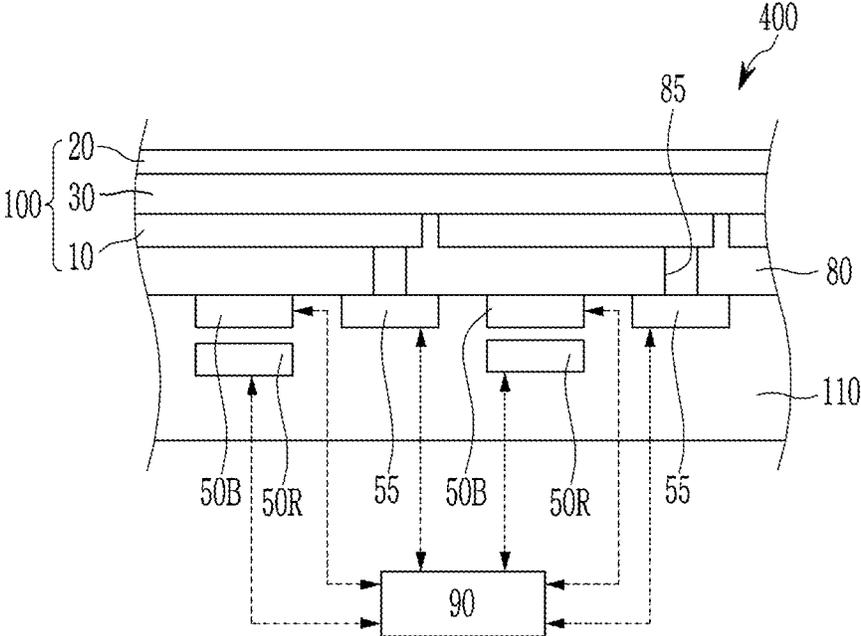


FIG. 7

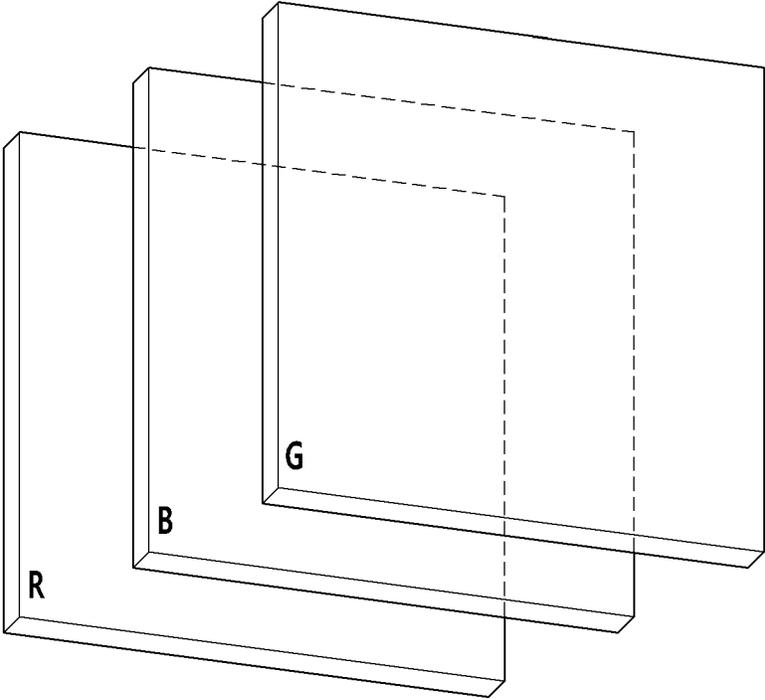


FIG. 8A

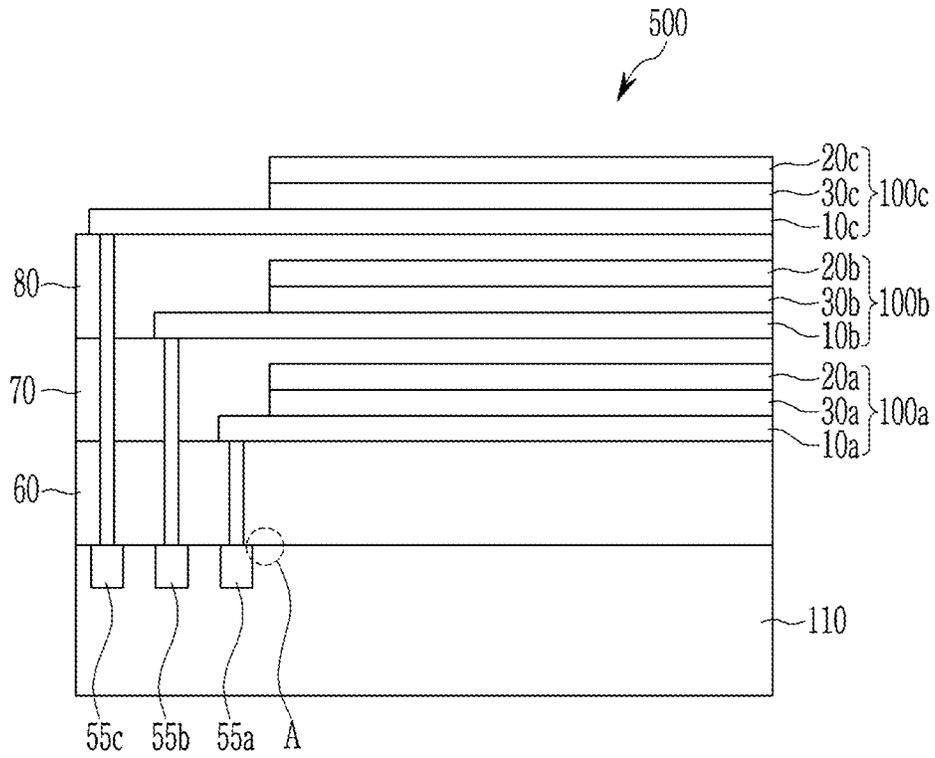


FIG. 8B

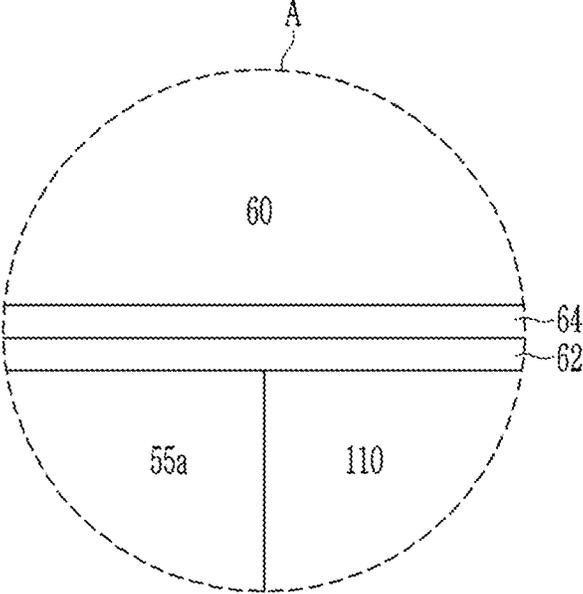


FIG. 9

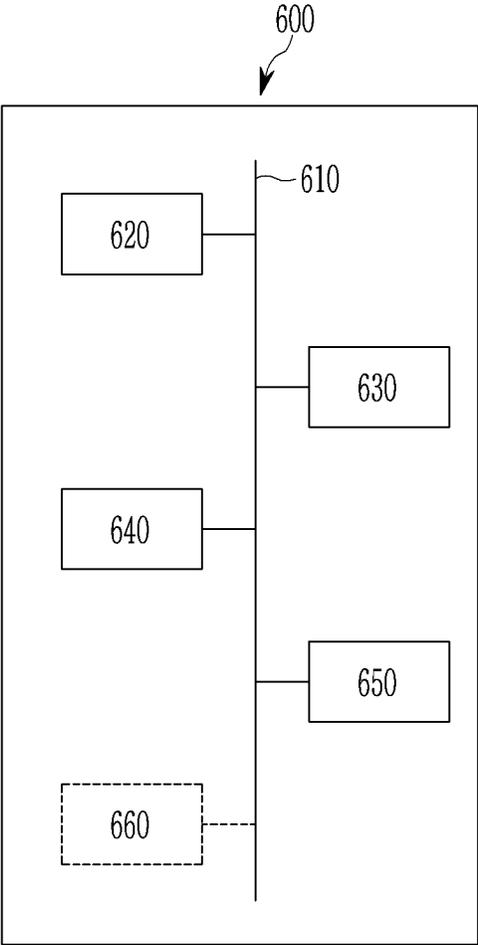


FIG. 10

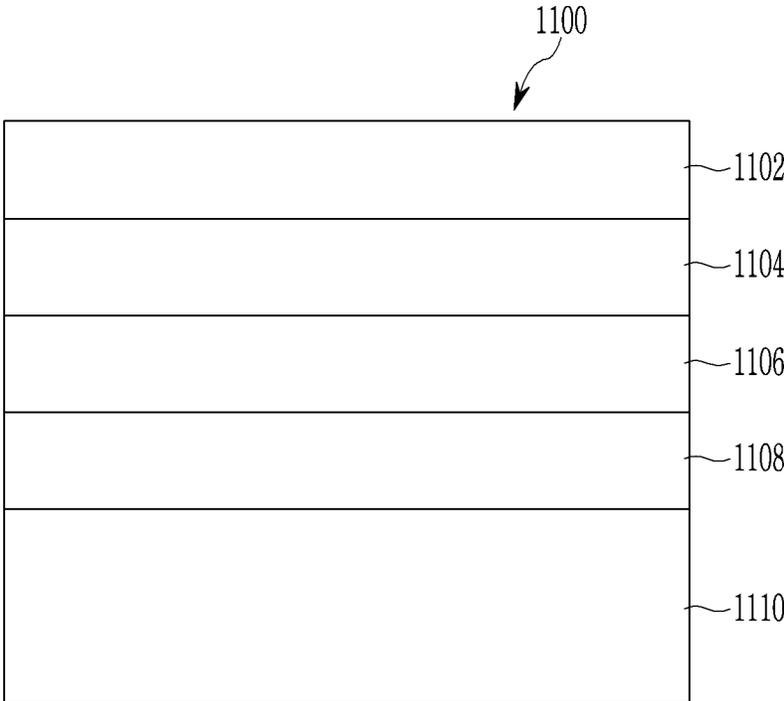


FIG. 11

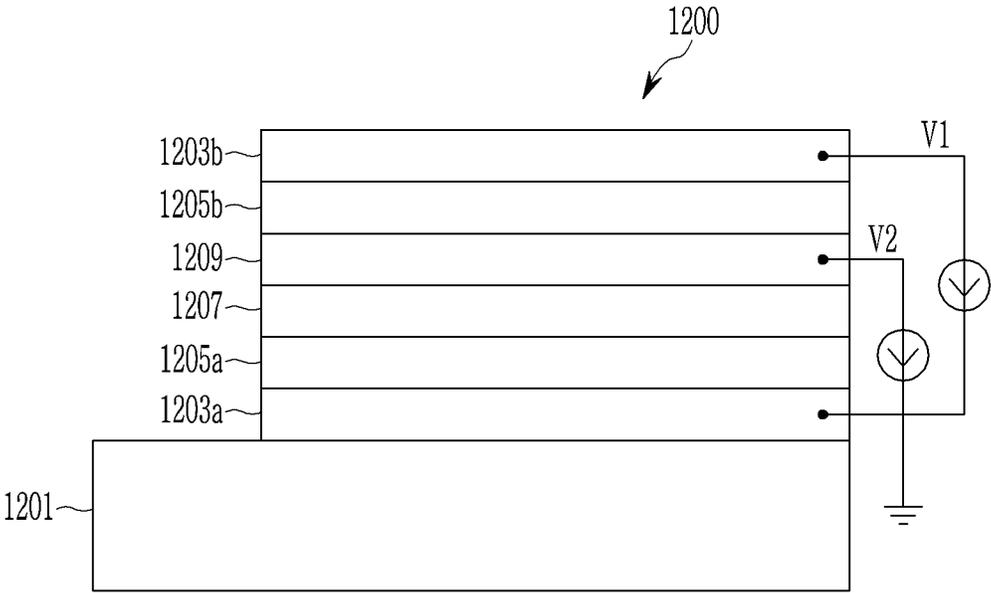
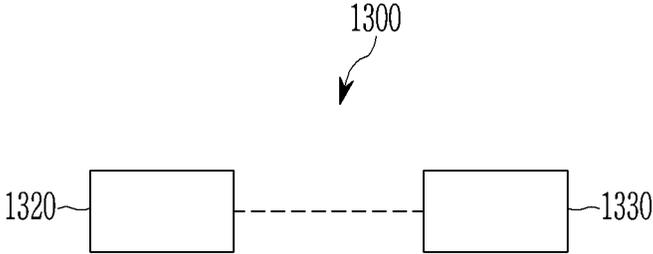


FIG. 12



ORGANIC PHOTOELECTRONIC DEVICE AND IMAGE SENSOR

CROSS-REFERENCE TO RELATED APPLICATION

This application claims priority to and the benefit of Korean Patent Application No. 10-2016-0081554 filed in the Korean Intellectual Property Office on Jun. 29, 2016, the entire contents of which are incorporated herein by reference.

BACKGROUND

1. Field

Example embodiments provide an organic photoelectric device and an image sensor including the same.

2. Description of the Related Art

A photoelectronic device may convert light into an electrical signal using photoelectric effects. A photoelectronic device may include a photodiode, a phototransistor, etc. A photoelectronic device may be applied to (e.g., included in) various devices, including image sensors, a solar cell, an organic light emitting diode, some combination thereof, etc.

An image sensor including a photodiode requires relatively high resolution and thus a smaller pixel. At present, a silicon photodiode is widely used. In some cases, a silicon photodiode exhibits a problem of deteriorated sensitivity because of a relatively small absorption area due to relatively small pixels. Accordingly, an organic material that is capable of replacing silicon has been researched.

An organic material has a relatively high extinction coefficient and selectively absorbs light in a particular wavelength region depending on a molecular structure, and thus may simultaneously replace a photodiode and a color filter and resultantly improve sensitivity and contribute to relatively high integration.

SUMMARY

Example embodiments provide an organic photoelectric device capable of increasing wavelength selectivity.

Example embodiments also provide an image sensor including the organic photoelectronic device.

Example embodiments also provide an electronic device including the image sensor.

According to example embodiments, an organic photoelectronic device includes a first electrode and a second electrode facing each other and a light-absorption layer between the first electrode and the second electrode and including a p-type light-absorbing material and an n-type light-absorbing material, wherein at least one of the p-type light-absorbing material and the n-type light-absorbing material selectively absorbs a part of visible light, and the light-absorption layer includes a photoelectric conversion region including the p-type light-absorbing material and the n-type light-absorbing material and a doped region including at least one of the p-type light-absorbing material and the n-type light-absorbing material, and an exciton quencher.

The photoelectric conversion region may include a first photoelectric conversion region near to the first electrode and a second photoelectric conversion region near to the

second electrode, and the doped region is between the first photoelectric conversion region and the second photoelectric conversion region.

The second electrode may be nearer to light incidence side than the first electrode, and a thickness of the second photoelectric conversion region may be the same as or larger than a thickness of the first photoelectric conversion region.

The exciton quencher may include a metal, a semi-metal, a metal oxide, a semi-metal oxide, an organic material, or a combination thereof.

The exciton quencher may include a hole transportable metal, a hole transportable semi-metal, a hole transportable metal oxide, a hole transportable semi-metal oxide, a hole transportable organic material, or a combination thereof.

The exciton quencher may include copper, silver, gold, aluminum, a molybdenum oxide, a tungsten oxide, a vanadium oxide, a rhenium oxide, a nickel oxide, or a combination thereof.

The exciton quencher may be included in an amount of less than or equal to about 50 volume % based on the amount of the doped region.

At least one of the p-type light-absorbing material and the n-type light-absorbing material may selectively absorb at least one of a wavelength of greater than or equal to about 400 nm and less than 500 nm, a wavelength region of about 500 nm to about 600 nm, and a wavelength region of greater than about 600 nm and less than or equal to about 700 nm.

The light-absorption layer may absorb first visible light and second visible light that are different wavelength regions from each other, and the first visible light may be absorbed at maximum in the photoelectric conversion region and the second visible light may be absorbed at maximum in the doped region.

One of the p-type light-absorbing material and the n-type light-absorbing material may selectively absorb the first visible light and the other of the p-type light-absorbing material and the n-type light-absorbing material may absorb the first visible light and the second visible light.

The first visible light may be a wavelength region of about 500 nm to about 600 nm and the second visible light may be a wavelength of greater than or equal to about 400 nm and less than 500 nm.

External quantum efficiency of the organic photoelectronic device for the first visible light and the second visible light may satisfy Relationship Equation 1.

$$EQE_{max}/EQE_{450\text{ nm}} \geq 3.80 \quad [\text{Relationship Equation 1}]$$

In Relationship Equation 1,

EQE_{max} is external quantum efficiency of the first visible light at a maximum absorption wavelength which is measured using an incident photon to current efficiency (IPCE), and

$EQE_{450\text{ nm}}$ is external quantum efficiency at 450 nm which is measured using an incident photon to current efficiency (IPCE).

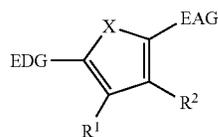
The p-type light-absorbing material may selectively absorb the first visible light and the n-type light-absorbing material may absorb the first visible light and the second visible light.

The n-type light-absorbing material may be fullerene or a fullerene derivative.

The p-type light-absorbing material may be an organic material including a core structure including an electron donating moiety, a pi conjugation linking group, and an electron accepting moiety.

The p-type light-absorbing material may be a compound represented by Chemical Formula 1.

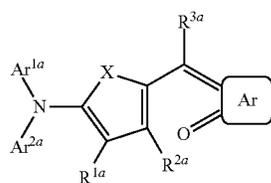
3



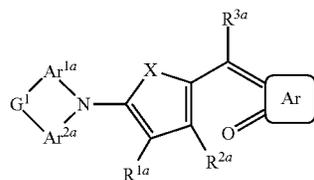
[Chemical Formula 1]

In Chemical Formula 1,
 X is Se, Te, SO, SO₂, or SiR^aR^b,
 EDG is an electron donating group,
 EAG is an electron accepting group, and
 R¹, R², R^a, and R^b are independently hydrogen or a
 monovalent substituent.

The p-type light-absorbing material may be a compound
 represented by Chemical Formula 1 A or 1B.



[Chemical Formula 1A]



[Chemical Formula 1B]

In Chemical Formula 1A or 1B,
 X is Se, Te, SO, SO₂, or SiR^aR^b,

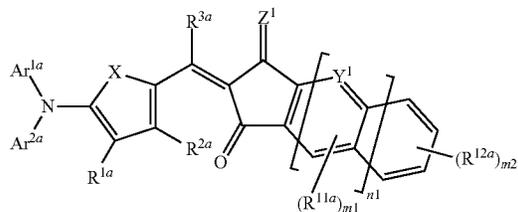
Ar is a substituted or unsubstituted 5-membered ring,
 a substituted or unsubstituted 6-membered ring, or a
 condensed ring of the two or more foregoing rings,

each of Ar^{1a} and Ar^{2a} are independently a substituted or
 unsubstituted C₆ to C₃₀ aryl group or a substituted or
 unsubstituted C₃ to C₃₀ heteroaryl group,

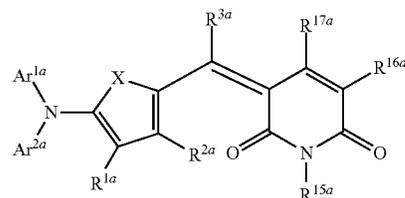
G¹ is selected from a single bond, —(CR^sR^t)_{n2}—,
 —O—, —S—, —Se—, —N=, —NRⁱ—, —SiR^jR^k—, and
 —Ge^lR^m—, wherein n₂ is 1 or 2, and

each of R^{1a} to R^{3a}, R^a, and R^b are independently hydro-
 gen, a substituted or unsubstituted C₁ to C₃₀ alkyl group,
 a substituted or unsubstituted C₆ to C₃₀ aryl group, a
 substituted or unsubstituted C₃ to C₃₀ heteroaryl group, a
 substituted or unsubstituted C₁ to C₆ alkoxy group, halogen, or a
 cyano group.

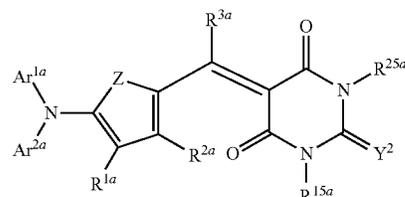
The p-type light-absorbing material may be a compound
 represented by one of Chemical Formulae 1A-1 to 1B-4.



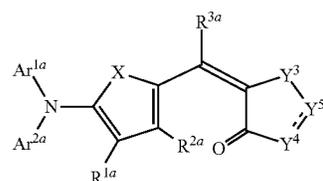
[Chemical Formula 1A-1]



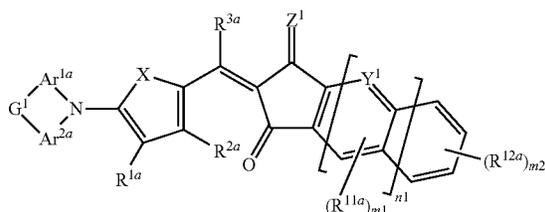
[Chemical Formula 1A-2]



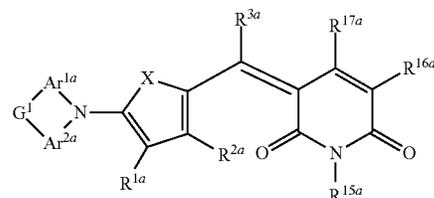
[Chemical Formula 1A-3]



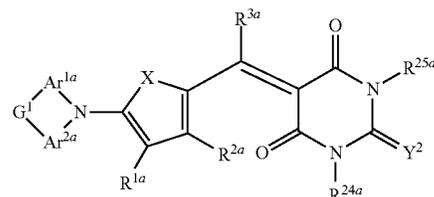
[Chemical Formula 1A-4]



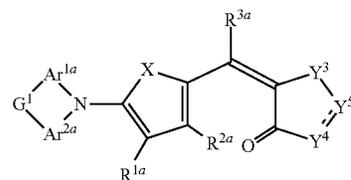
[Chemical Formula 1B-1]



[Chemical Formula 1B-2]



[Chemical Formula 1B-3]



[Chemical Formula 1B-4]

In Chemical Formulae 1A-1 to 1B-4,
 X is Se, Te, SO, SO₂, or SiR^cR^b,
 Z¹ is O or CR^cR^d,
 Y¹ is N or CR^e,
 Y² is selected from O, S, Se, Te, and C(R^f)(CN),
 Y³ is O, S, Se, or Te,
 Y⁴ is N or NR^{18a},
 Y⁵ is CR^{19a} or C=CR^{20a}(CN),

each of Ar^{1a} and Ar^{2a} are independently a substituted or unsubstituted C₆ to C₃₀ aryl group or a substituted or unsubstituted C₃ to C₃₀ heteroaryl group,

each of R^{1a} to R^{3a}, R^{11a}, R^{12a}, R^{15a} to R^{20a}, R^{24a}, R^{25a}, and R^a to R^f are independently hydrogen, a substituted or unsubstituted C₁ to C₃₀ alkyl group, a substituted or unsubstituted C₆ to C₃₀ aryl group, a substituted or unsubstituted C₃ to C₃₀ heteroaryl group, a substituted or unsubstituted C₁ to C₆ alkoxy group, a halogen, or a cyano group,

n1 is 0 or 1,

m1 is 0 or 1, and

m2 is an integer of 0 to 4.

According to example embodiments, an image sensor includes the organic photoelectronic device.

According to example embodiments, an electronic device includes the image sensor.

BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1 is a cross-sectional view showing an organic photoelectronic device according to example embodiments,

FIG. 2 is a cross-sectional view showing one example of the organic photoelectronic device of FIG. 1,

FIG. 3 is a cross-sectional view showing an organic photoelectronic device according to example embodiments,

FIG. 4 is a schematic top plan view showing an organic CMOS image sensor according to example embodiments,

FIG. 5A is a cross-sectional view showing one example of the CMOS image sensor of FIG. 4,

FIG. 5B is a cross-section view of a portion A of the image sensor 300 illustrated in FIG. 5A,

FIG. 6 is a cross-sectional view showing another example of an organic CMOS image sensor of FIG. 4,

FIG. 7 is a schematic top plan view showing an organic CMOS image sensor according to example embodiments, and

FIG. 8A is a cross-sectional view of an organic CMOS image sensor of FIG. 7 and FIG. 8B is a cross-sectional view of a portion A of the image sensor 500 illustrated in FIG. 8A.

FIG. 9 is a diagram illustrating an electronic device 600 according to some example embodiments,

FIG. 10 is a cross-sectional view showing a solar cell according to some example embodiments,

FIG. 11 is a sectional view of an organic light-emitting display apparatus according to some example embodiments, and

FIG. 12 is a view showing a sensor according to some example embodiments.

DETAILED DESCRIPTION

Example embodiments will hereinafter be described in detail, and may be easily performed by those who have common knowledge in the related art. However, this disclosure may be embodied in many different forms and is not to be construed as limited to the example embodiments set forth herein.

In the drawings, the thickness of layers, films, panels, regions, etc., are exaggerated for clarity. It will be under-

stood that when an element such as a layer, film, region, or substrate is referred to as being “on” another element, it can be directly on the other element or intervening elements may also be present. In contrast, when an element is referred to as being “directly on” another element, there are no intervening elements present.

Although the terms “first,” “second,” “third,” etc., may be used herein to describe various elements, components, regions, layers, and/or sections, these elements, components, regions, layers, and/or sections, should not be limited by these terms. These terms are only used to distinguish one element, component, region, layer, or section, from another region, layer, or section. Thus, a first element, component, region, layer, or section, discussed below may be termed a second element, component, region, layer, or section, without departing from the scope of this disclosure.

Spatially relative terms, such as “beneath,” “below,” “lower,” “under,” “above,” “upper,” etc., may be used herein for ease of description to describe one element or feature’s relationship to another element(s) or feature(s) as illustrated in the figures. It will be understood that the spatially relative terms are intended to encompass different orientations of the device in use or operation in addition to the orientation depicted in the figures. For example, if the device in the figures is turned over, elements described as “below,” “beneath,” or “under,” other elements or features would then be oriented “above” the other elements or features. Thus, the example terms “below” and “under” may encompass both an orientation of above and below. The device may be otherwise oriented (rotated 90 degrees or at other orientations) and the spatially relative descriptors used herein interpreted accordingly. In addition, when an element is referred to as being “between” two elements, the element may be the only element between the two elements, or one or more other intervening elements may be present.

As used herein, the singular forms “a,” “an,” and “the,” are intended to include the plural forms as well, unless the context clearly indicates otherwise. It will be further understood that the terms “comprises” and/or “comprising,” when used in this specification, specify the presence of stated features, integers, steps, operations, elements, and/or components, but do not preclude the presence or addition of one or more other features, integers, steps, operations, elements, components, and/or groups, thereof. As used herein, the term “and/or” includes any and all combinations of one or more of the associated listed items. Expressions such as “at least one of,” when preceding a list of elements, modify the entire list of elements and do not modify the individual elements of the list. Also, the term “exemplary” is intended to refer to an example or illustration.

When an element is referred to as being “on,” “connected to,” “coupled to,” or “adjacent to,” another element, the element may be directly on, connected to, coupled to, or adjacent to, the other element, or one or more other intervening elements may be present. In contrast, when an element is referred to as being “directly on,” “directly connected to,” “directly coupled to,” or “immediately adjacent to,” another element, there are no intervening elements present.

Unless otherwise defined, all terms (including technical and scientific terms) used herein have the same meaning as commonly understood by one of ordinary skill in the art to which example embodiments belong. Terms, such as those defined in commonly used dictionaries, should be interpreted as having a meaning that is consistent with their meaning in the context of the relevant art and/or this

disclosure, and should not be interpreted in an idealized or overly formal sense unless expressly so defined herein.

In the drawings, parts having no relationship with the description are omitted for clarity of the embodiments, and the same or similar constituent elements are indicated by the same reference numerals throughout the specification.

Hereinafter, an organic photoelectronic device according to example embodiments is described with reference to drawings.

FIG. 1 is a cross-sectional view showing an organic photoelectronic device according to example embodiments, and FIG. 2 is a cross-sectional view showing one example of the organic photoelectronic device of FIG. 1.

Referring to FIG. 1, an organic photoelectronic device 100 according to example embodiments includes a first electrode 10 and a second electrode 20 facing each other and a light-absorption layer 30 between the first electrode 10 and the second electrode 20.

One of the first electrode 10 and the second electrode 20 is an anode, and the other is a cathode. At least one of the first electrode 10 and second electrode 20 may be a light-transmitting electrode, and the light-transmitting electrode may at least partially comprise, for example, a transparent conductor including an indium tin oxide (ITO) or an indium zinc oxide (IZO), or a metal thin layer of a thin monolayer or multilayer. When one of the first electrode 10 and the second electrode 20 is a non-light-transmitting electrode, the first electrode 10 or the second electrode 20 may at least partially comprise, for example, an opaque conductor such as aluminum (Al).

For example, the first electrode 10 and the second electrode 20 are light-transmitting electrodes.

The light-absorption layer 30 includes a p-type light-absorbing material and an n-type light-absorbing material and thereby absorbs light in a given or predetermined wavelength region to generate excitons and then to separate the generated excitons into holes and electrons.

At least one of the p-type light-absorbing material and the n-type light-absorbing material selectively absorbs a part of visible light, and for example at least one of the p-type light-absorbing material and the n-type light-absorbing material may selectively absorb light of one of a wavelength of greater than or equal to about 400 nm and less than 500 nm, a wavelength region of about 500 nm to about 600 nm, and a wavelength region of greater than about 600 nm and less than or equal to about 700 nm. That is, at least one of the p-type light-absorbing material and the n-type light-absorbing material may selectively absorb one of green light, blue light, and red light.

For example, one of the p-type light-absorbing material and the n-type light-absorbing material may selectively absorb one of green light, blue light, and red light, and the other of the p-type light-absorbing material and the n-type light-absorbing material may absorb two or more of green light, blue light, and red light.

For example, one of the p-type light-absorbing material and the n-type light-absorbing material may selectively absorb green light, and the other of the p-type light-absorbing material and the n-type light-absorbing material may absorb blue light and/or red light as well as green light.

For example, one of the p-type light-absorbing material and the n-type light-absorbing material may selectively absorb red light, and the other of the p-type light-absorbing material and the n-type light-absorbing material may absorb blue light and/or green light as well as red light.

For example, one of the p-type light-absorbing material and the n-type light-absorbing material may selectively

absorb blue light, and the other of the p-type light-absorbing material and the n-type light-absorbing material may absorb red light and/or green light as well as blue light.

For example, the p-type light-absorbing material may selectively absorb green light, and the n-type light-absorbing material may absorb blue light and/or red light as well as green light.

For example, the n-type light-absorbing material may selectively absorb green light, and the p-type light-absorbing material may absorb blue light and/or red light as well as green light.

For example, the p-type light-absorbing material may selectively absorb red light, and the n-type light-absorbing material may absorb blue light and/or green light as well as red light.

For example, the n-type light-absorbing material may selectively absorb red light, and the p-type light-absorbing material may absorb blue light and/or green light as well as red light.

For example, the p-type light-absorbing material may selectively absorb blue light, and the n-type light-absorbing material may absorb green light and/or red light as well as blue light.

For example, the n-type light-absorbing material may selectively absorb blue light, and the p-type light-absorbing material may absorb green light and/or red light as well as blue light.

The light-absorption layer 30 includes a photoelectric conversion region that generates excitons by light in given or predetermined wavelength region absorbed by the p-type light-absorbing material and the n-type light-absorbing material, and then separates the generated excitons into holes and electrons.

The light-absorption layer 30 includes a doped region including an exciton quencher that reduces or suppresses photoelectric conversion. The doped region may be disposed inside the light-absorption layer 30, for example, between the photoelectric conversion regions.

The doped region of the light-absorption layer 30 may include at least one of a p-type light-absorbing material and an n-type light-absorbing material on which the exciton quencher is doped. For example, the doped region of the light-absorption layer 30 may include a p-type light-absorbing material and an exciton quencher. For example, the doped region of the light-absorption layer 30 may include an n-type light-absorbing material and an exciton quencher. For example, the doped region of the light-absorption layer 30 may include a p-type light-absorbing material, an n-type light-absorbing material, and an exciton quencher. The exciton quencher may be included in an amount of less than or equal to about 50 volume %, for example about 0.1 volume % to about 50 volume %, about 1 volume % to about 40 volume %, about 5 volume % to about 40 volume % based on the doped region.

The exciton quencher is not particularly limited as long as it may reduce and/or suppress generation of excitons or reduce and/or suppress activity of excitons by removing energy from excitons, and may be, for example a metal, a semi-metal, a metal oxide, a semi-metal oxide, an organic material, or a combination thereof.

The exciton quencher may be, for example a hole transportable exciton quencher, for example a hole transportable metal, a hole transportable semi-metal, a hole transportable metal oxide, a hole transportable semi-metal oxide, a hole transportable organic material, or a combination thereof. Herein, hole transporting capability refers to characteristics to donate electrons by receiving light and to form or trans-

port holes, and to have conduction characteristics along a HOMO energy level and to make holes be transferred easily. The hole transportable exciton quencher may have, for example a work function of greater than or equal to about 4.5 eV or a HOMO energy level of greater than or equal to about 5.0 eV, but is not limited thereto.

The exciton quencher may be, for example, copper, silver, gold, aluminum, a molybdenum oxide, a tungsten oxide, a vanadium oxide, a rhenium oxide, a nickel oxide, or a combination thereof, but is not limited thereto.

The exciton quencher may be, for example an electron transportable exciton quencher and may be, for example an electron transportable metal, an electron transportable semi-metal, an electron transportable metal oxide, an electron transportable semi-metal oxide, an electron transportable organic material, or a combination thereof. Herein, electron transporting capability refers to characteristics to accept electrons by receiving light and to have conduction characteristics along an LUMO energy level and to make electrons be transferred easily. The electron transportable exciton quencher may be, for example a material having a work function of less than about 4.5 eV or an LUMO energy level of less than or equal to about 4.5 eV, but is not limited thereto.

The exciton quencher may be, for example a manganese oxide, a titanium oxide, a zinc oxide, or a combination thereof, but is not limited thereto.

For example, referring to FIG. 2, the light-absorption layer 30 may include a first photoelectric conversion region 30a near to the first electrode 10, a second photoelectric conversion region 30b near to the second electrode 20, and a doped region 30c disposed between the first photoelectric conversion region 30a and the second photoelectric conversion region 30b. That is, the first photoelectric conversion region 30a, the doped region 30c, and the second photoelectric conversion region 30b may be sequentially disposed along a thickness direction of the light-absorption layer 30.

The first photoelectric conversion region 30a and the second photoelectric conversion region 30b may respectively include a p-type light-absorbing material and an n-type light-absorbing material, and the p-type light-absorbing material and the n-type light-absorbing material may be mixed in a form of a bulk heterojunction. The first photoelectric conversion region 30a and the second photoelectric conversion region 30b may respectively include, a p-type light-absorbing material and an n-type light-absorbing material in a volume ratio of, for example, about 1:10 to about 10:1, about 2:8 to about 8:2, about 3:7 to about 7:3, or about 4:6 to about 6:4.

The doped region 30c may include at least one of the p-type light-absorbing material and the n-type light-absorbing material, and an exciton quencher. For example, the doped region 30c may include a mixture of the p-type light-absorbing material and the exciton quencher. For example, the doped region 30c may include a mixture of the p-type light-absorbing material, the n-type light-absorbing material, and the exciton quencher. When the doped region 30c includes the p-type light-absorbing material, the n-type light-absorbing material, and the exciton quencher, in the doped region 30c, a composition ratio of the p-type light-absorbing material and the n-type light-absorbing material may be the same as in the first photoelectric conversion region 30a and the second photoelectric conversion region 30b. The exciton quencher may be included in an amount of less than or equal to about 50 volume %, for

example about 0.1 volume % to about 50 volume %, about 1 volume % to about 40 volume %, about 5 volume % to about 40 volume % based on the doped region 30c.

The doped region 30c may have a thickness of about 1 nm to about 50 nm, for example about 5 nm to about 40 nm, or about 10 nm to about 30 nm.

A sum of thicknesses of the first photoelectric conversion region 30a and the second photoelectric conversion region 30b may be greater than a thickness of the doped region 30c. The thicknesses of the first photoelectric conversion region 30a and the second photoelectric conversion region 30b are not particularly limited, and for example a photoelectric conversion region near to a light receiving side may have a sufficient thickness. For example, when the second electrode 20 is nearer than the first electrode 10 to a light receiving side, a thickness of the second photoelectric conversion region 30b may be the same or greater than that of the first photoelectric conversion region 30a.

The doped region 30c includes the exciton quencher and thereby activity of excitons generated the p-type light-absorbing material and/or the n-type light-absorbing material in the doped region 30c may be reduced and/or suppressed to reduce photoelectric conversion efficiency of absorbed light in the doped region 30c.

The light-absorption layer 30 may mainly absorb light in different wavelength regions depending on a position, for example, along the thickness direction. For example, green light may be mainly absorbed in a near region to the incident side of the light-absorption layer 30, and blue light may be mainly absorbed in a middle region of the light-absorption layer 30.

In example embodiments, considering that a light-absorbing region of the light-absorption layer 30 varies depending on a visible ray wavelength region, the doped region 30c including an exciton quencher may be formed in a region mainly absorbing light of an undesired region to decrease photoelectric conversion efficiency in the undesired wavelength region and thus increase wavelength selectivity of an organic photoelectric device.

For example, when the light-absorption layer 30 mainly absorbs green light of an about 500 nm to about 600 nm wavelength region, which is a desired wavelength region, the light of the about 500 nm to about 600 nm wavelength region is absorbed at most in the first and second photoelectric conversions region 30a and 30b, and light of the other wavelength regions may be absorbed at most in the doped region 30c.

Specifically, external quantum efficiency (EQE) of the organic photoelectric device 100 may be proportional to absorbance and internal quantum efficiency (IQE) of the light-absorption layer 30, and the internal quantum efficiency (IQE) may be classified into charge separation efficiency (CS) and charge collection efficiency (CC).

In example embodiments, absorbance and charge separation efficiency of light of a desired wavelength region may be secured by including a p-type light-absorbing material and an n-type light-absorbing material in a composition ratio capable of exerting an optimal efficiency in a region absorbing the light of the desired wavelength region, and simultaneously, charge separation efficiency of light of an undesired wavelength region may be decreased by forming the doped region 30c where an exciton quencher is doped in a region absorbing the light of the undesired region. Accordingly, external quantum efficiency (EQE) of the light of the desired wavelength region may be secured, and simultaneously, wavelength selectivity of the light of the undesired wavelength region may be increased.

11

On the other hand, the exciton quencher may have charge transfer characteristics like the hole transportable exciton quencher or an electron transportable exciton quencher as described above. Accordingly, the exciton quencher may increase mobility of holes separated from the first and second photoelectric conversion regions **30a** and **30b** toward an anode, either one of the first electrode **10** and second electrode **20**, while the holes are passing the doped region **30c** and also, mobility of electrons separated from the first and second photoelectric conversion regions **30a** and **30b** toward a cathode, either one of the first electrode **10** and the second electrode **20**, while the electrons are passing the doped region **30c**. In particular, when the exciton quencher is a hole transportable exciton quencher, mobility between the electrons and the holes in the light-absorption layer **30** may be balanced by increasing mobility of the holes generally having lower mobility than electrons.

Accordingly, the organic photoelectric device according to example embodiments may realize relatively high efficiency by increasing charge mobility as well as wavelength selectivity.

For example, the wavelength selectivity may be for example calculated as an external quantum efficiency (EQE) ratio of light of a desired wavelength region and light of an undesired wavelength region. For example, when the light-absorption layer **30** is a green light-absorption layer that mainly absorbs light in a wavelength region of about 500 nm to about 600 nm and one of the p-type light-absorbing material and the n-type light-absorbing material selectively absorbs first visible light in a wavelength region of about 500 nm to about 600 nm and the other of the p-type light-absorbing material and the n-type light-absorbing material absorbs second visible light in a wavelength region of greater than or equal to about 400 nm and less than about 500 nm as well as the first visible light in a wavelength region of about 500 nm to about 600 nm, external quantum efficiency of the organic photoelectric device for the first visible light and the second visible light may satisfy Relationship Equation 1.

$$EQE_{max}/EQE_{450\text{ nm}} \geq 3.80 \quad [\text{Relationship Equation 1}]$$

In Relationship Equation 1,

EQE_{max} is external quantum efficiency of the first visible light at a maximum absorption wavelength which is measured using an incident photon to current efficiency (IPCE), and

$EQE_{450\text{ nm}}$ is external quantum efficiency at 450 nm which is measured using an incident photon to current efficiency (IPCE).

For example, within the range, for example it may satisfy Relationship Equation 1a.

$$EQE_{max}/EQE_{450\text{ nm}} \geq 3.85 \quad [\text{Relationship Equation 1a}]$$

For example, within the range, for example it may satisfy Relationship Equation 1b.

$$EQE_{max}/EQE_{450\text{ nm}} \geq 4.00 \quad [\text{Relationship Equation 1 b}]$$

For example, wavelength selectivity may be expressed as a full width at half maximum (FWHM). The full width at half maximum (FWHM) refers to a width of a wavelength corresponding to half of a maximum absorption point in a light absorption curve depending on a wavelength, and may be for example defined by absorbance measured by UV-Vis spectroscopy. The light-absorption layer **30** may have, for example a full width at half maximum (FWHM) of less than about 110 nm, for example less than or equal to about 105 nm or less than or equal to about 100 nm.

12

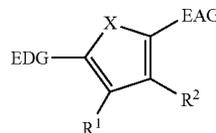
For example, the p-type light-absorbing material of the light-absorption layer **30** may selectively absorb the first visible light in a wavelength region of about 500 nm to about 600 nm and the n-type light-absorbing material may absorb the first visible light in a wavelength region of about 500 nm to about 600 nm and the second visible light in a wavelength region of greater than or equal to about 400 nm and less than about 500 nm.

For example, the p-type light-absorbing material of the light-absorption layer **30** may be, for example quinacridone or a derivative thereof, sub-phthalocyanine or a derivative thereof and the n-type light-absorbing material may be fullerene or a fullerene derivative.

For example, the p-type light-absorbing material of the light-absorption layer **30** is for example an organic material having a core structure including an electron donating moiety, a pi conjugation linking group, and an electron accepting moiety, and the n-type light-absorbing material may be fullerene or a fullerene derivative.

For example, the p-type light-absorbing material of the light-absorption layer **30** may be, for example a compound represented by Chemical Formula 1.

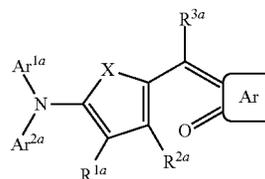
[Chemical Formula 1]



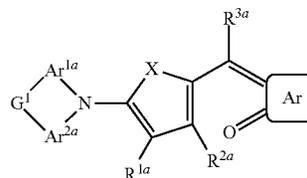
In Chemical Formula 1, X is Se, Te, SO, SO₂, or SiR^aR^b, EDG is an electron donating group, EAG is an electron accepting group, and R¹, R², R^a, and R^b are independently hydrogen or a monovalent substituent.

The p-type light-absorbing material may be, for example a compound represented by Chemical Formula 1A or 1B.

[Chemical Formula 1A]



[Chemical Formula 1B]



In Chemical Formula 1A or 1B, X is Se, Te, SO, SO₂, or SiR^aR^b, Ar is a substituted or unsubstituted 5-membered ring, a substituted or unsubstituted 6-membered ring, or a condensed ring of the two or more foregoing rings, Ar^{1a} and Ar^{2a} are independently a substituted or unsubstituted C₆ to C₃₀ aryl group or a substituted or unsubstituted C₃ to C₃₀ heteroaryl group,

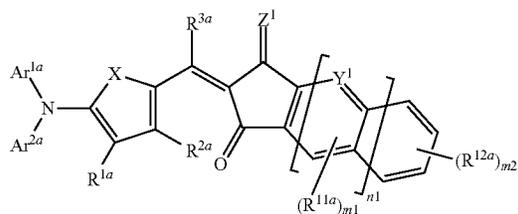
13

G^1 is selected from a single bond, $-(CR^gR^h)_{n2}-$, $-O-$, $-S-$, $-Se-$, $-N=$, $-NR^i-$, $-SiR^jR^k-$, and $-GeR^lR^m-$, wherein $n2$ is 1 or 2, and

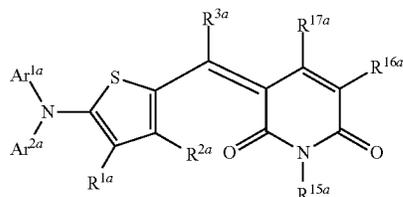
each of R^{1a} to R^{3a} , R^a , and R^b are independently hydrogen, a substituted or unsubstituted C_1 to C_{30} alkyl group, a substituted or unsubstituted C_6 to C_{30} aryl group, a substituted or unsubstituted C_3 to C_{30} heteroaryl group, a substituted or unsubstituted C_1 to C_6 alkoxy group, halogen, or a cyano group.

The p-type light-absorbing material may be, for example a compound represented by one of Chemical Formulae 1A-1 to 1A-4.

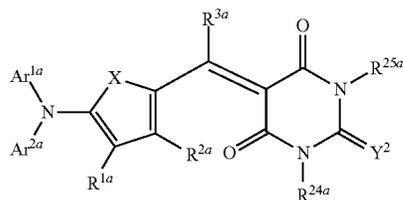
[Chemical Formula 1A-1]



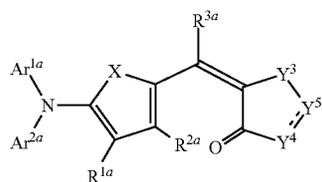
[Chemical Formula 1A-2]



[Chemical Formula 1A-3]



[Chemical Formula 1A-4]



In Chemical Formulae 1A-1 to 1A-4,

X is Se, Te, SO, SO_2 , or SiR^aR^b ,

Z^1 is O or CR^cR^d ,

Y^1 is N or CR^e ,

Y^2 is selected from O, S, Se, Te, and $C(R^f)(CN)$,

Y^3 is O, S, Se, or Te,

Y^4 is N or NR^{18a} ,

Y^5 is CR^{19a} or $C=CR^{20a}(CN)$,

each of Ar^{1a} and Ar^{2a} are independently a substituted or unsubstituted C_6 to C_{30} aryl group or a substituted or unsubstituted C_3 to C_{30} heteroaryl group,

each of R^{1a} to R^{3a} , R^{11a} , R^{12a} , R^{15a} to R^{20a} , R^{24a} , R^{25a} , and R^a to R^f are independently hydrogen, a substituted or unsubstituted C_1 to C_{30} alkyl group, a substituted or unsubstituted C_6 to C_{30} aryl group, a substituted or unsubstituted

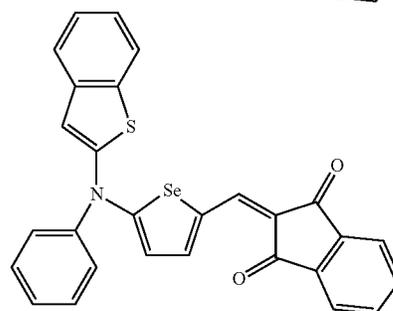
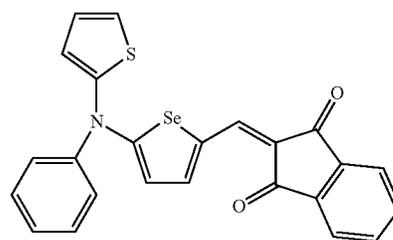
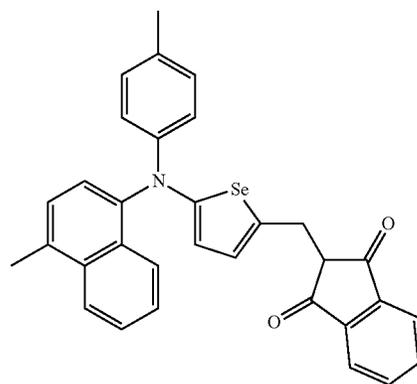
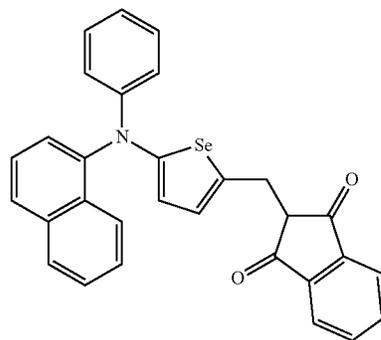
14

C_3 to C_{30} heteroaryl group, a substituted or unsubstituted C_1 to C_6 alkoxy group, a halogen, or a cyano group, and

$n1$ is 0 or 1, $m1$ is 0 or 1, and $m2$ is an integer of 0 to 4.

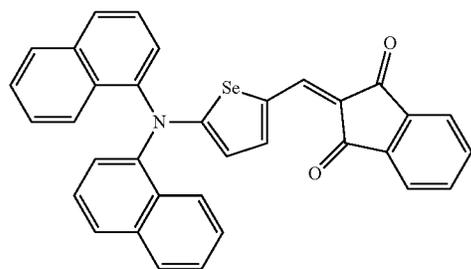
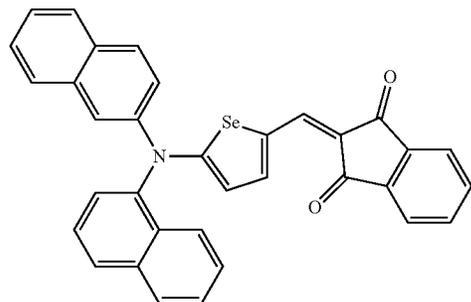
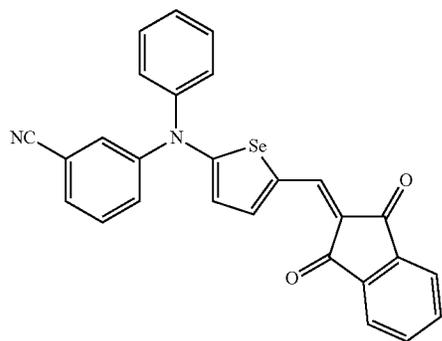
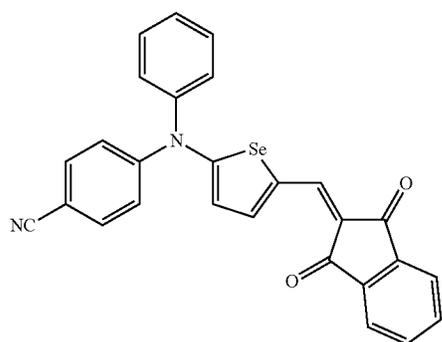
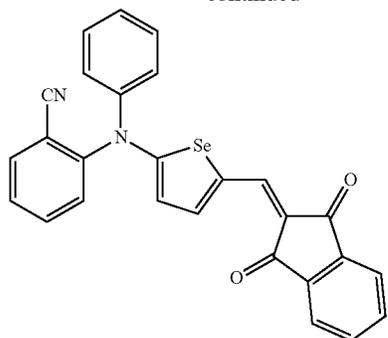
The compound represented by one of Chemical Formulae 1A-1 to 1A-4 may be, for example compounds of Group 1, but is not limited thereto.

[Group 1]



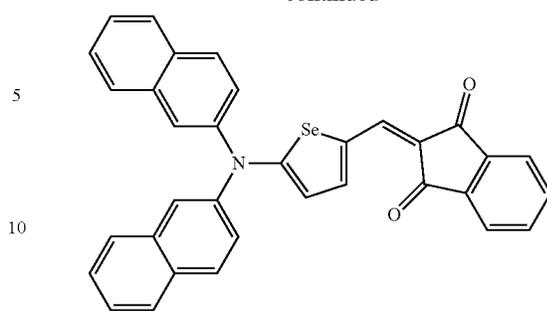
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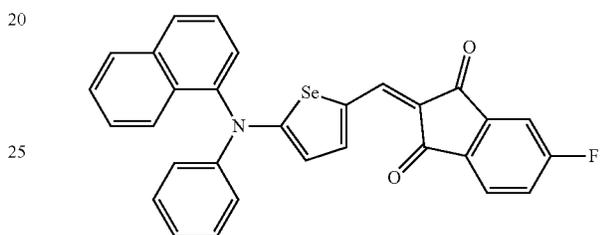


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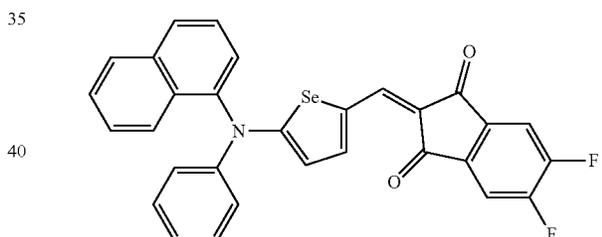
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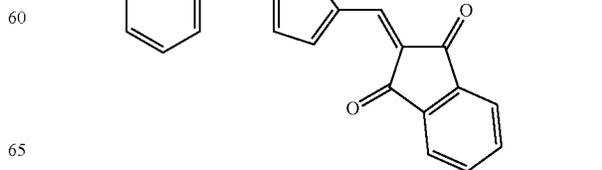
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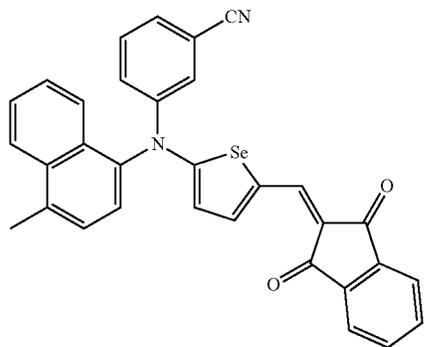
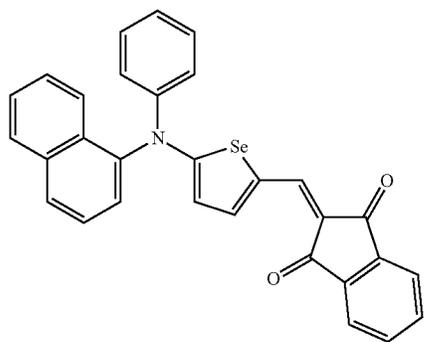
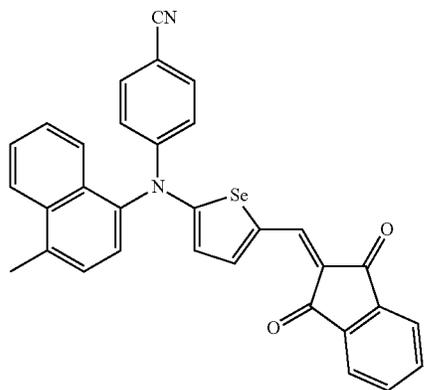
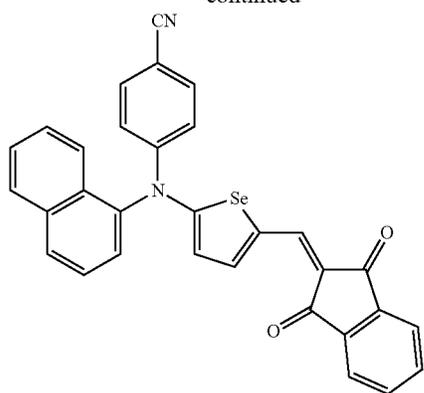
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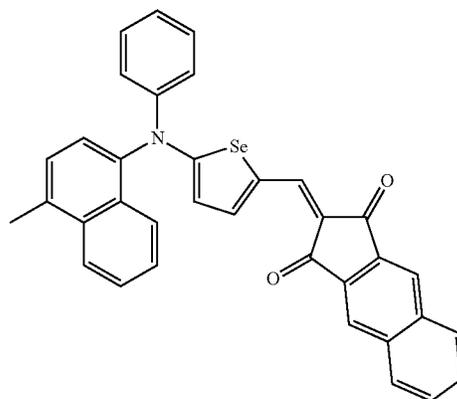
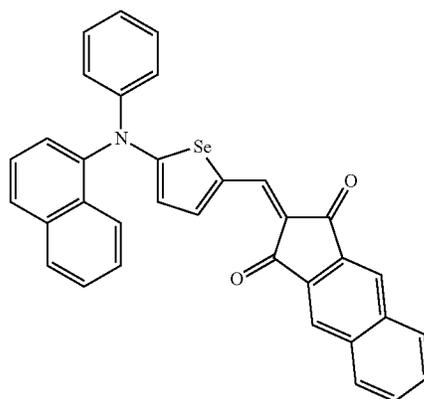
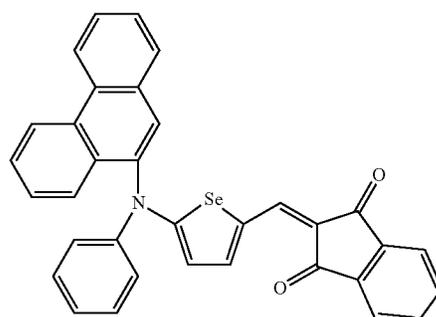
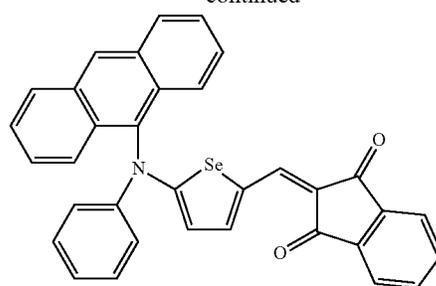
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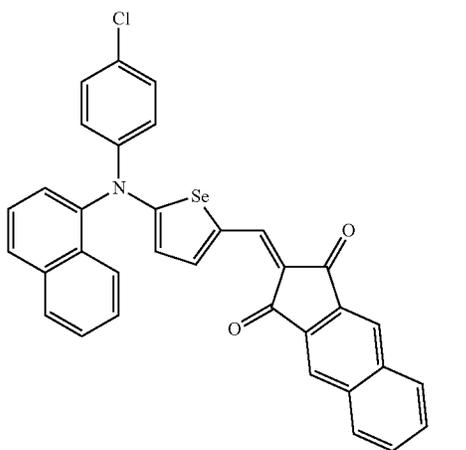
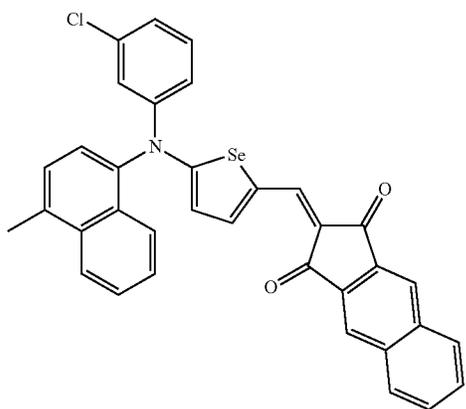
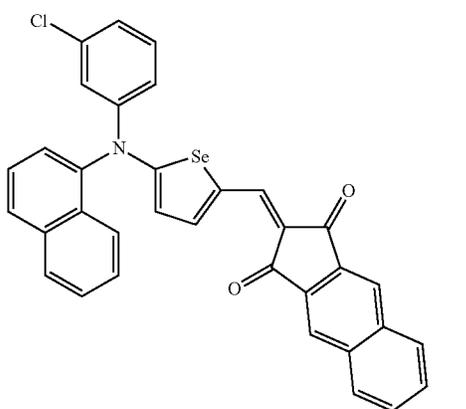
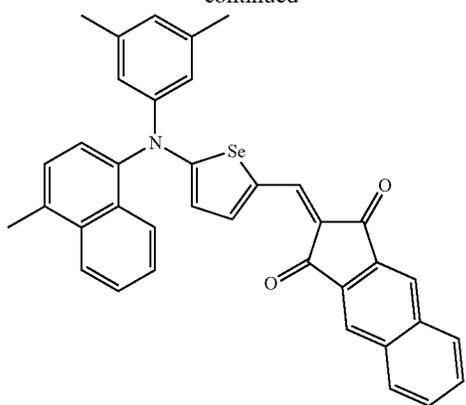
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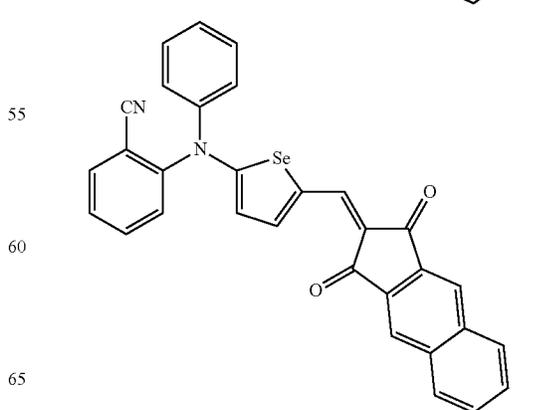
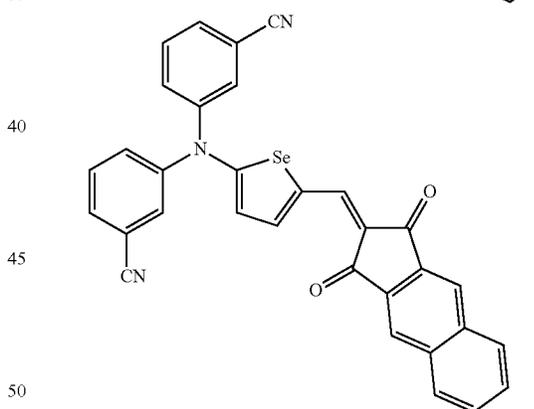
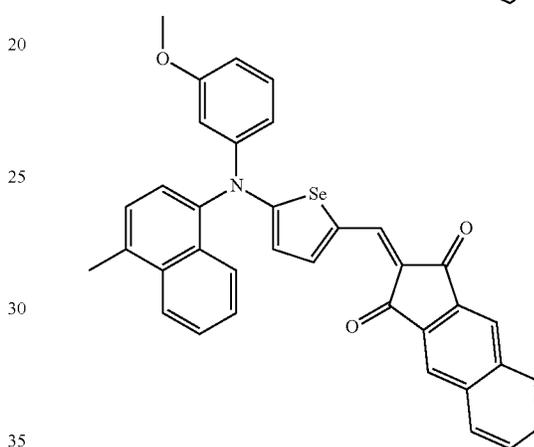
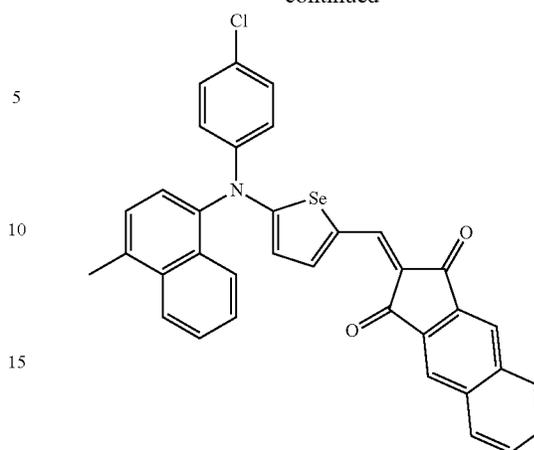
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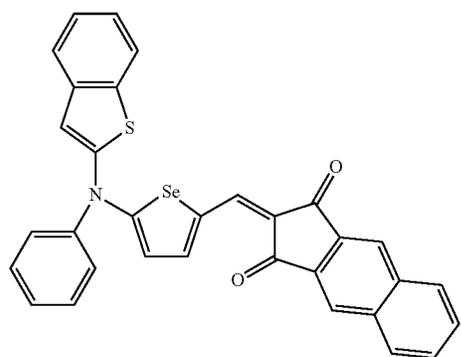
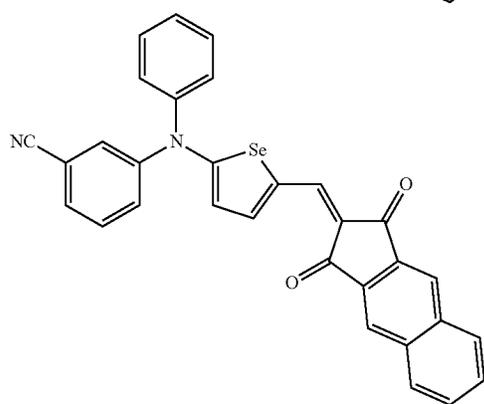
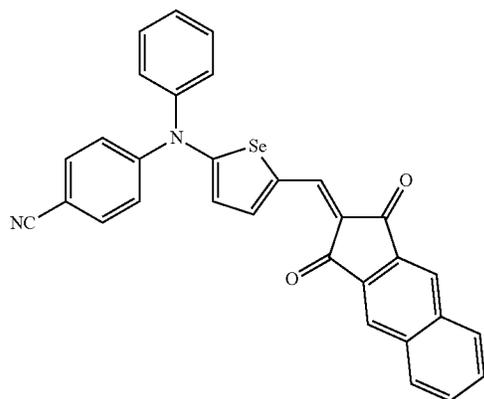
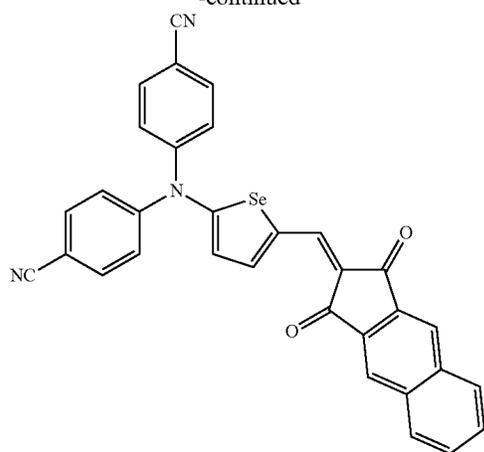
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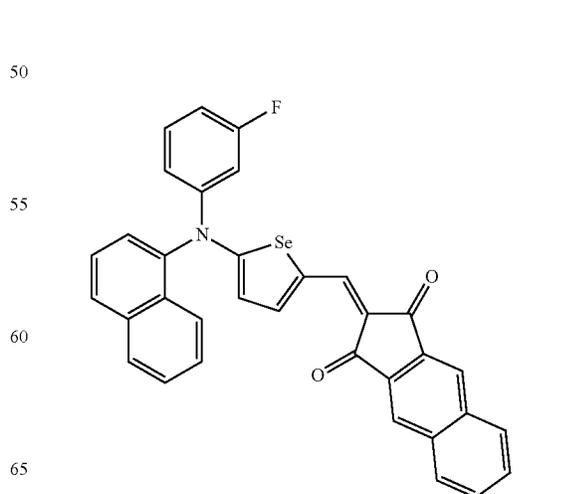
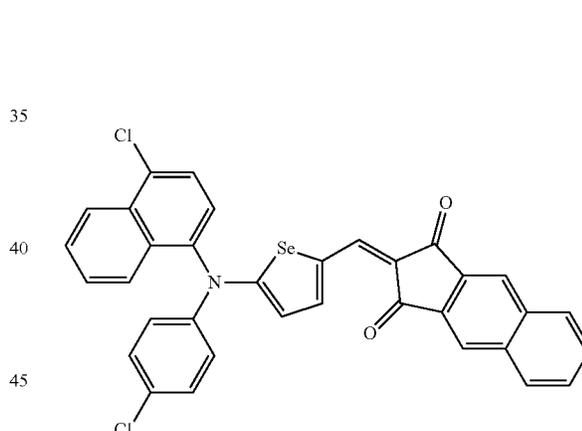
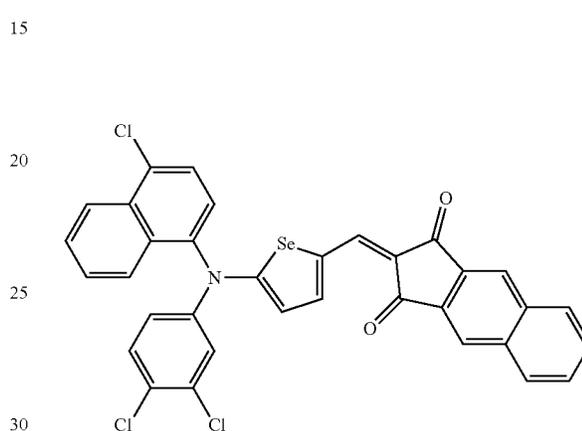
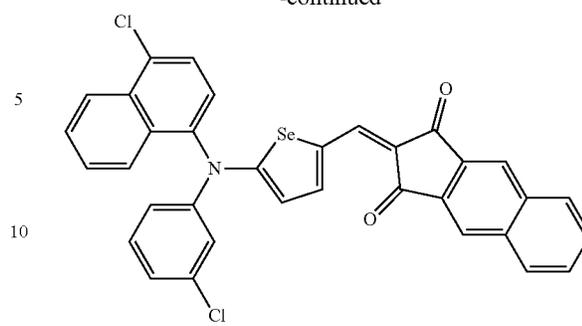
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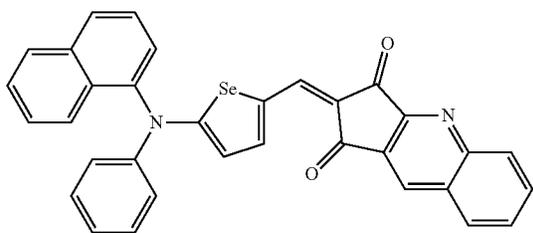
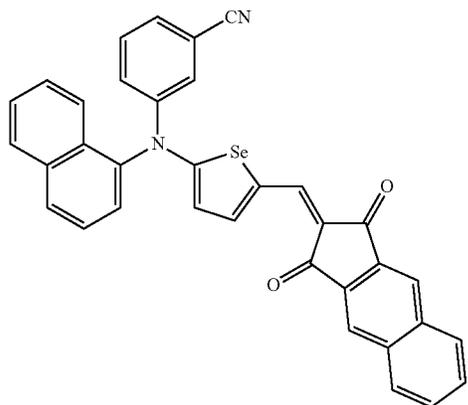
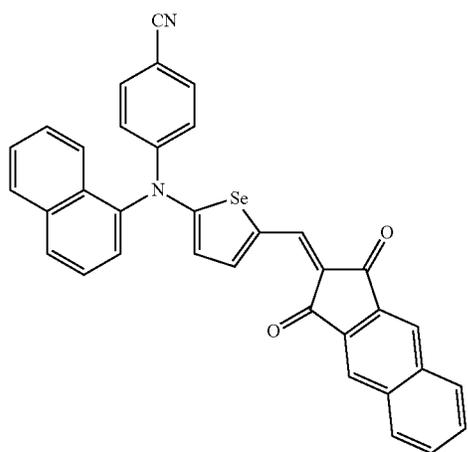
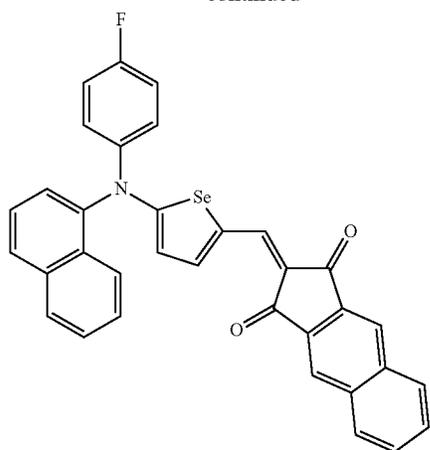
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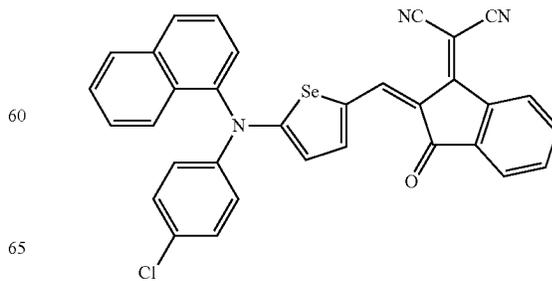
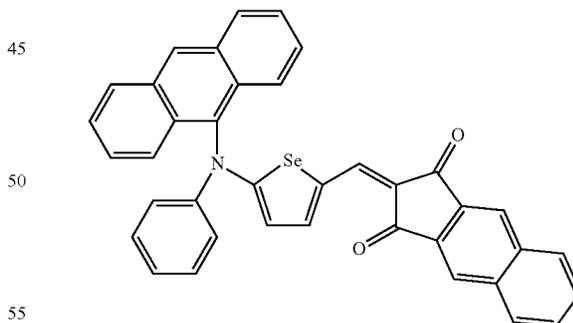
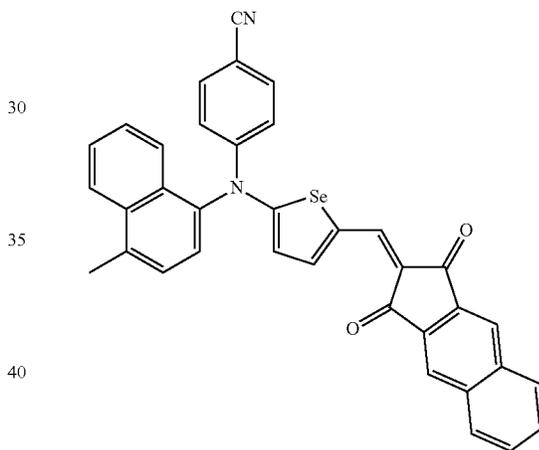
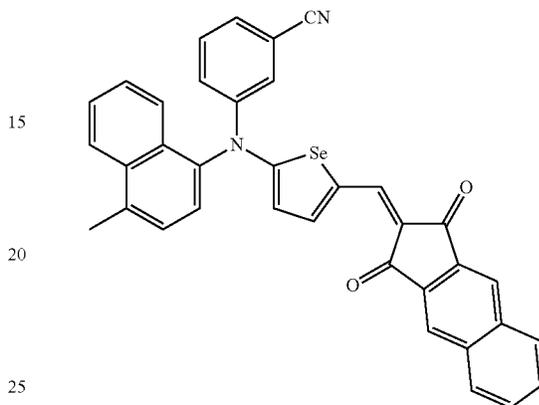
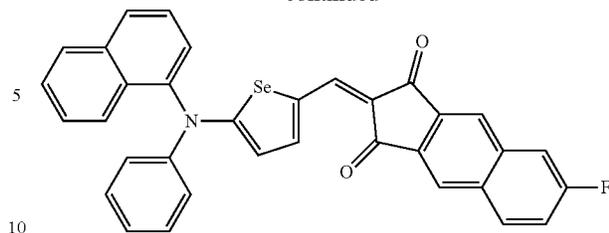
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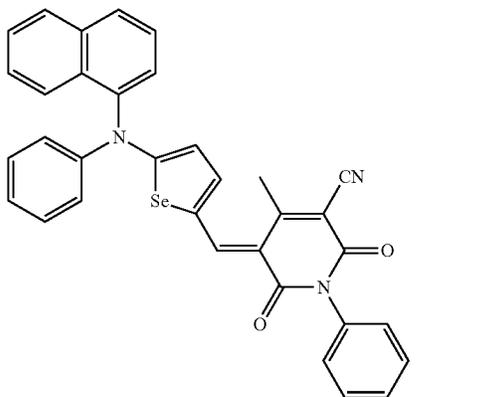
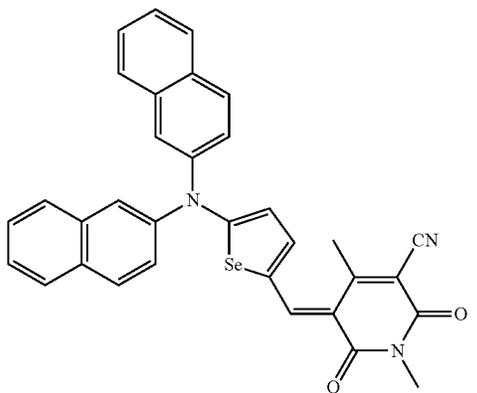
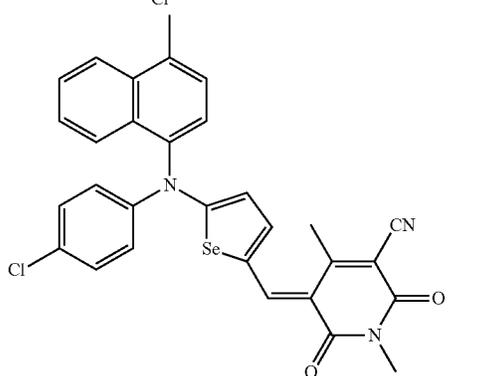
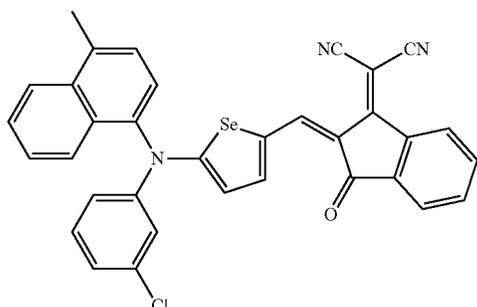
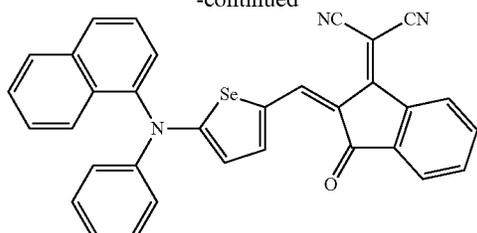
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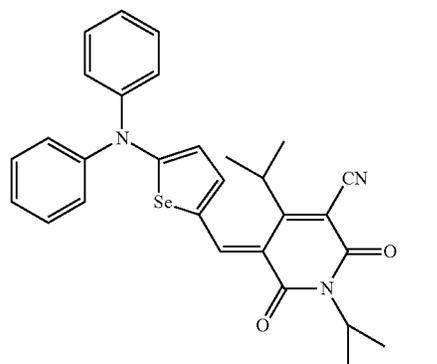
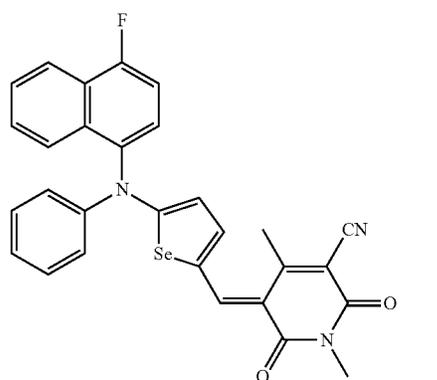
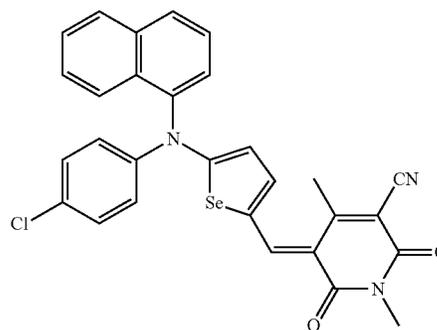
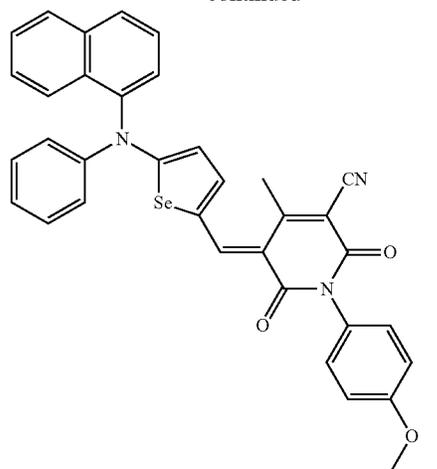
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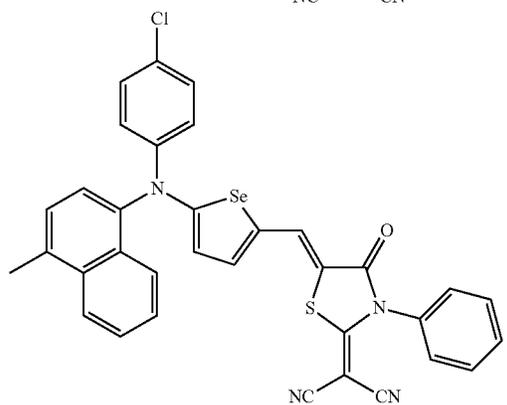
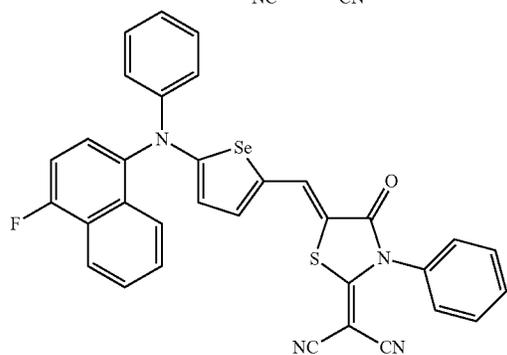
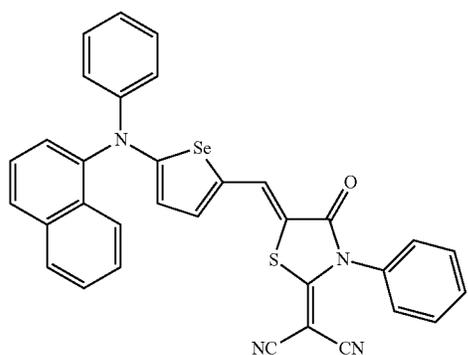
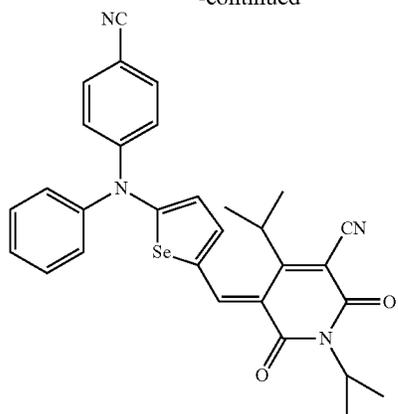
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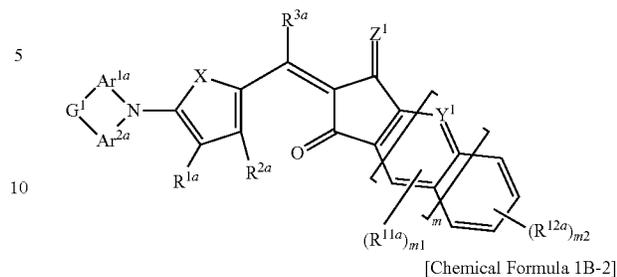
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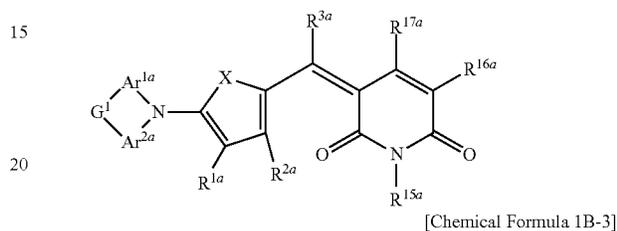
The p-type light-absorbing material may be, for example a compound represented by one of Chemical Formulae 1B-1 to 1B-4.

28

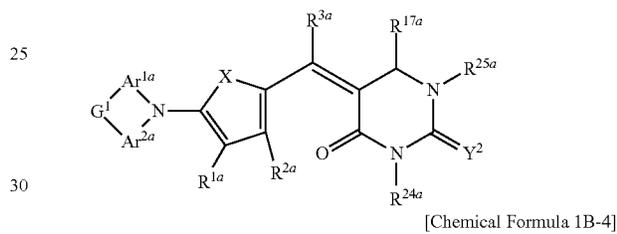
[Chemical Formula 1B-1]



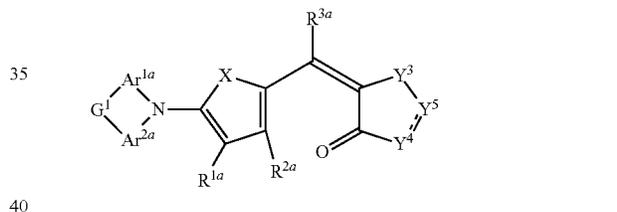
[Chemical Formula 1B-2]



[Chemical Formula 1B-3]



[Chemical Formula 1B-4]



In Chemical Formulae 1B-1 to 1B-4,

X is Se, Te, SO, SO₂, or SiR^aR^b,

Z¹ is O or CR^cR^d,

Y¹ is N or CR^e,

Y² is selected from O, S, Se, Te, and C(R^f)(CN),

Y³ is O, S, Se, or Te,

Y⁴ is N or NR^{18a},

Y⁵ is CR^{19a} or C=CR^{20a}(CN),

Ar^{1a} and Ar^{2a} are independently a substituted or unsubstituted C₆ to C₃₀ aryl group or a substituted or unsubstituted C₃ to C₃₀ heteroaryl group,

G¹ is selected from a single bond, —(CR^gR^h)_{m2}—, —O—, —S—, —Se—, —N—, —NRⁱ—, —SiR^jR^k—, and —GeR^lR^m—, wherein n2 is 1 or 2,

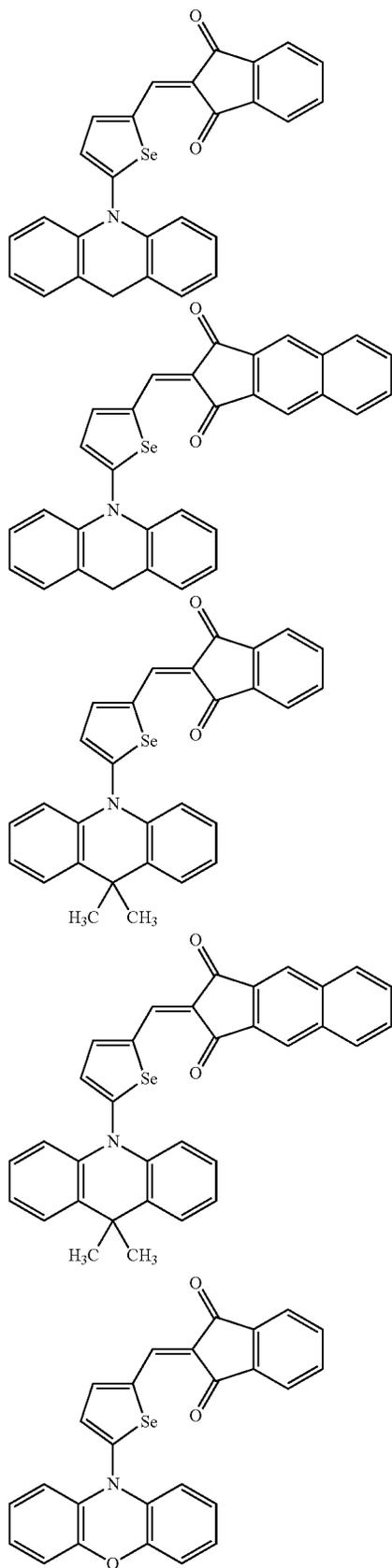
R^{1a} to R^{3a}, R^{11a}, R^{12a}, R^{15a} to R^{20a}, R^{24a}, R^{25a}, and R^a to R^m are independently hydrogen, a substituted or unsubstituted C₁ to C₃₀ alkyl group, a substituted or unsubstituted C₆ to C₃₀ aryl group, a substituted or unsubstituted C₃ to C₃₀ heteroaryl group, a substituted or unsubstituted C₁ to C₆ alkoxy group, a halogen, or a cyano group,

n1 is 0 or 1, n2 is 0, 1 or 2, m1 is 0 or 1, and m2 is an integer of 0 to 4.

The compound represented by one of Chemical Formulae 1B-1 to 1B-4 may be, for example compounds of Group 2, but is not limited thereto.

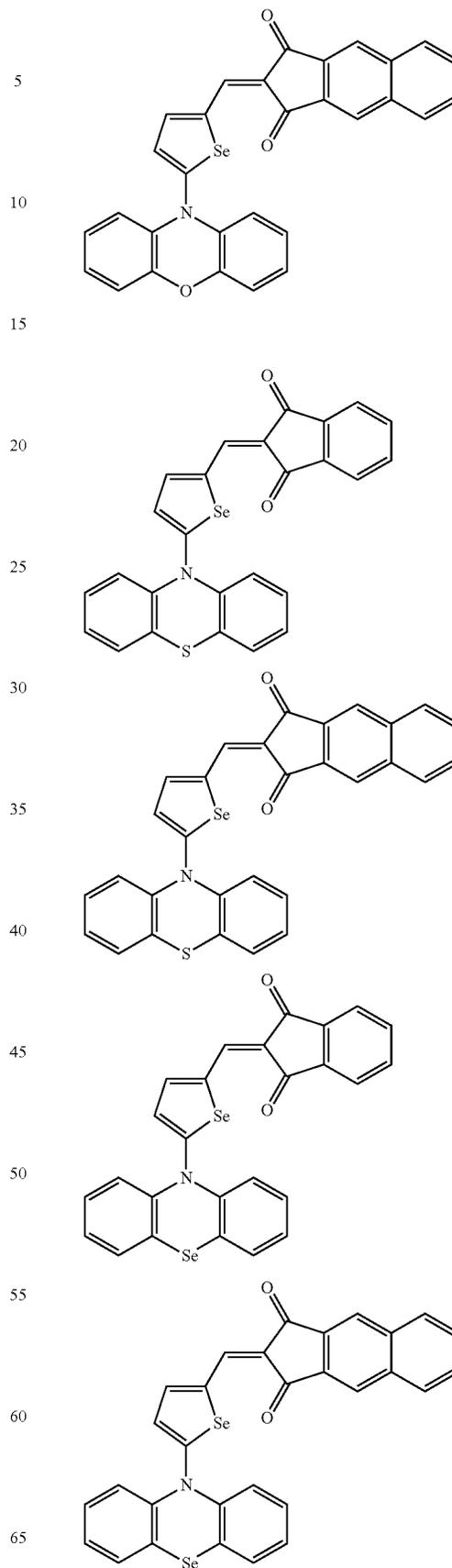
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[Group 2]



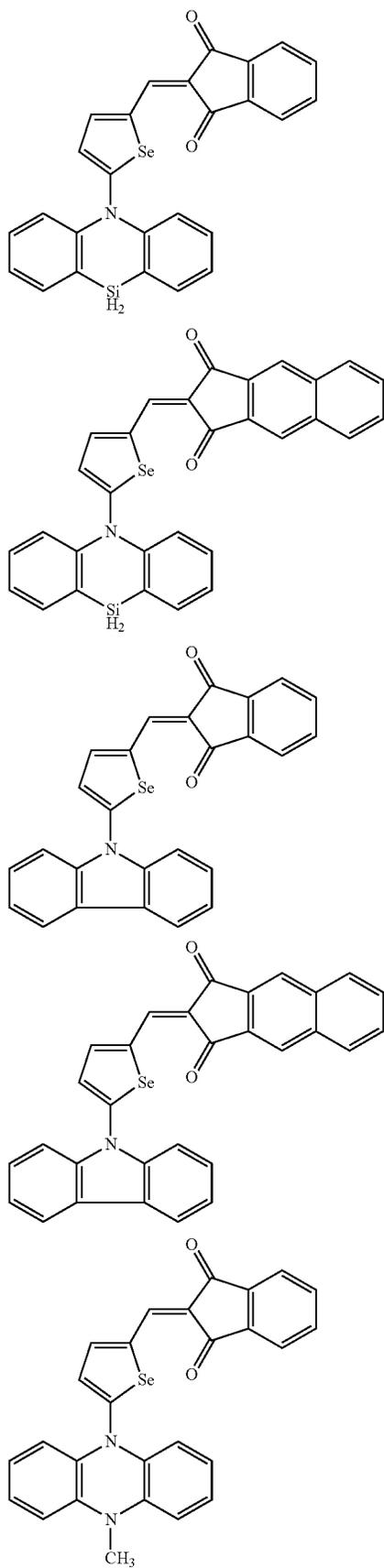
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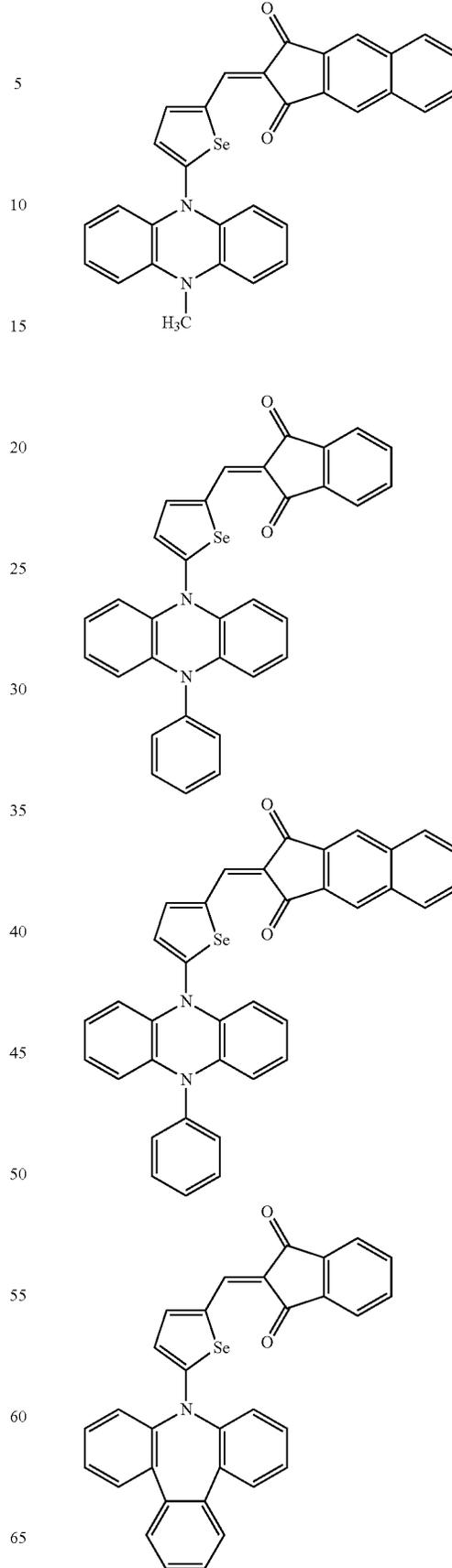
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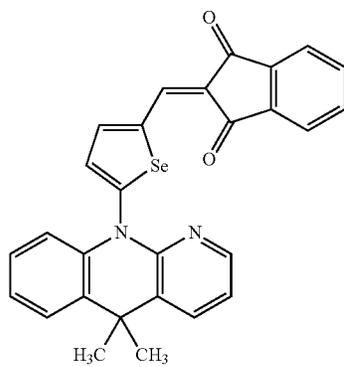
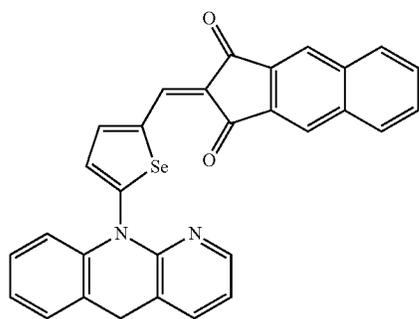
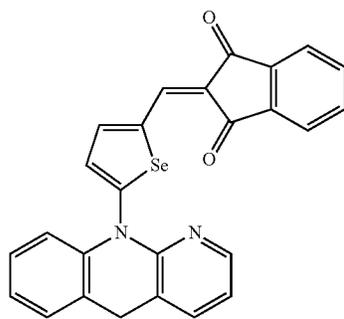
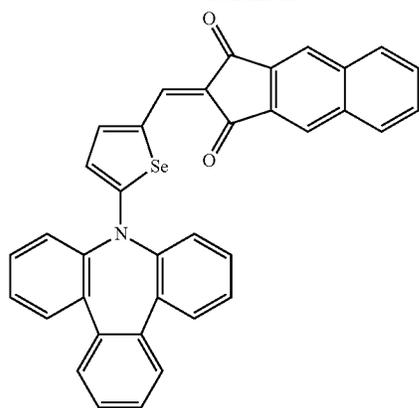
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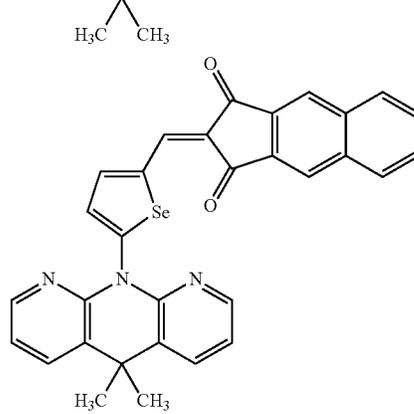
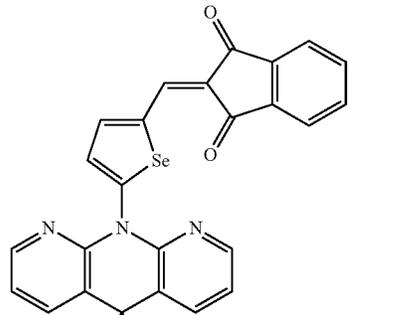
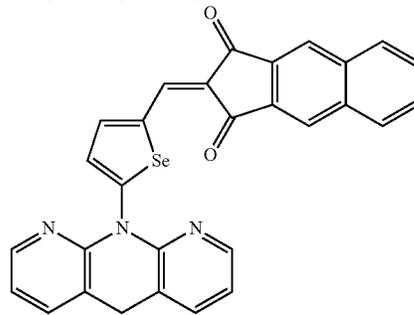
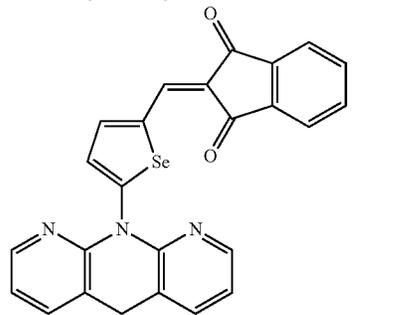
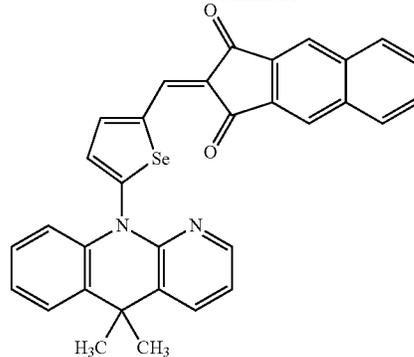
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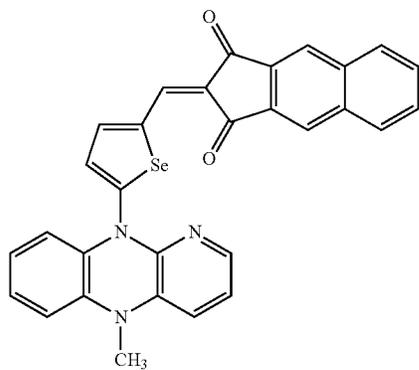
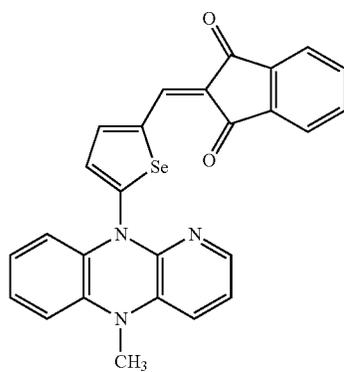
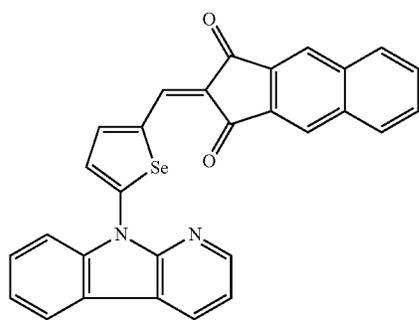
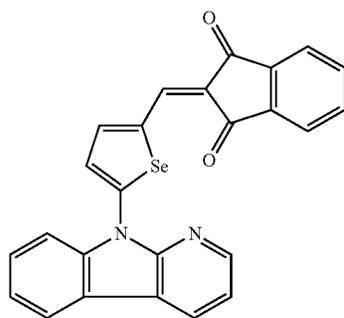
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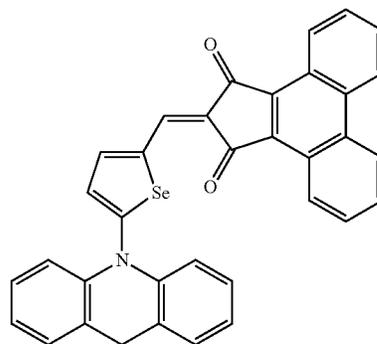
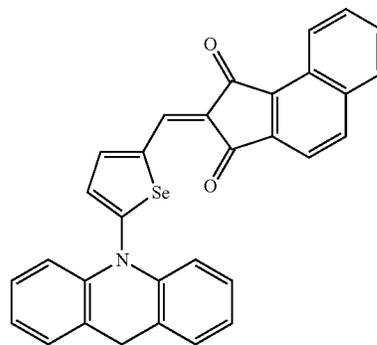
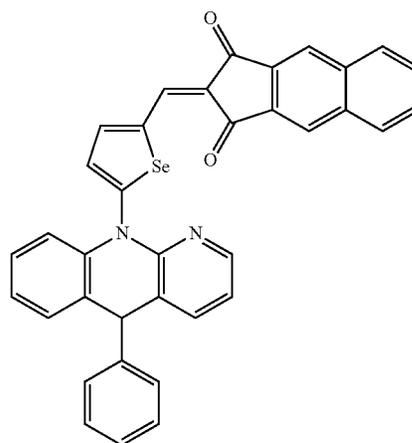
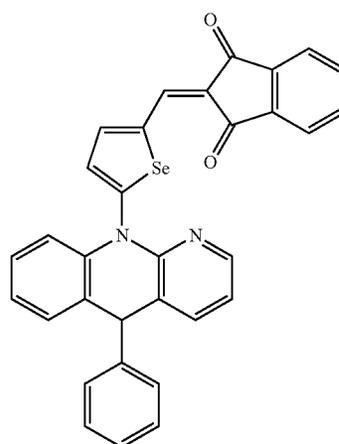
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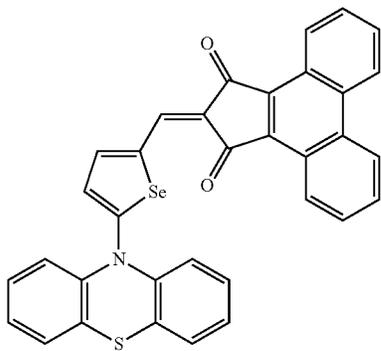
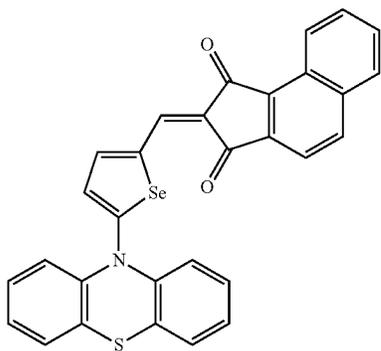
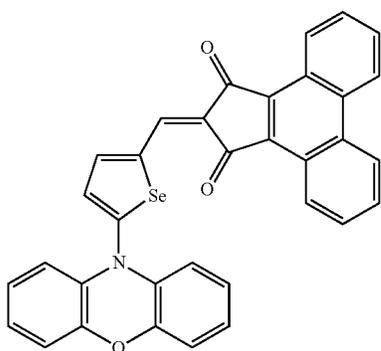
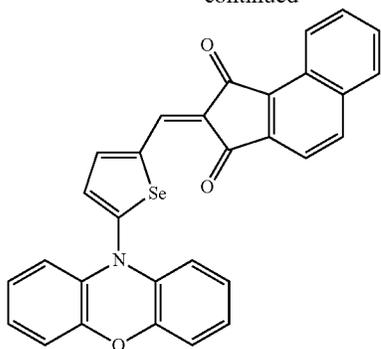
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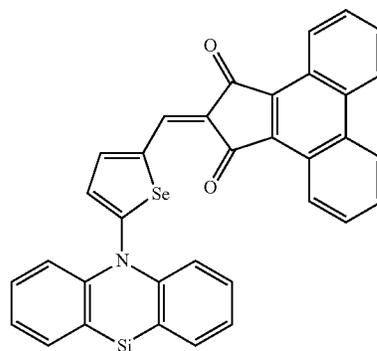
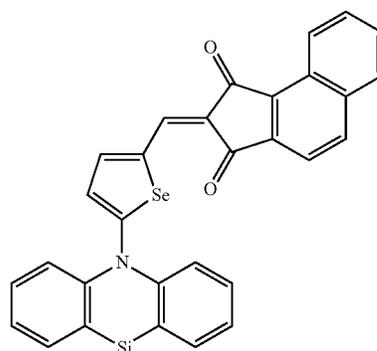
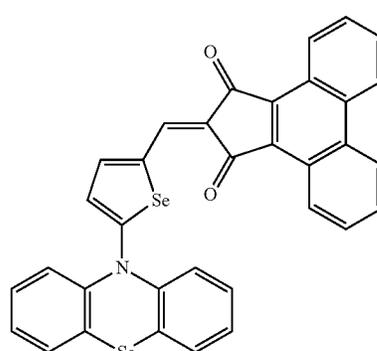
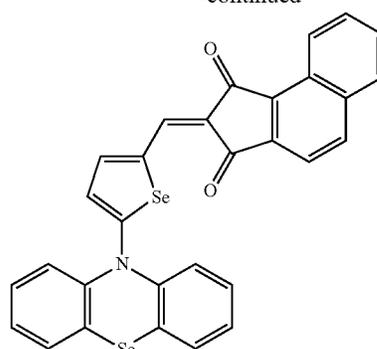
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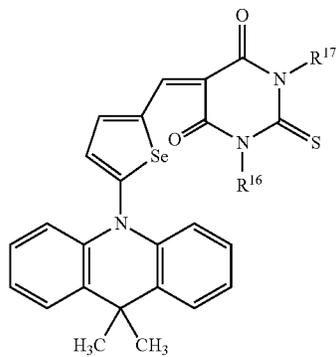
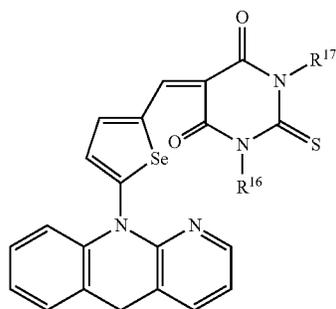
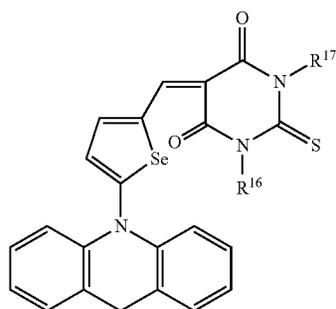
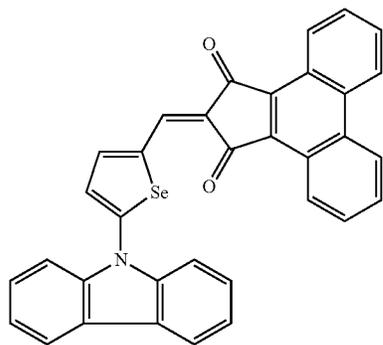
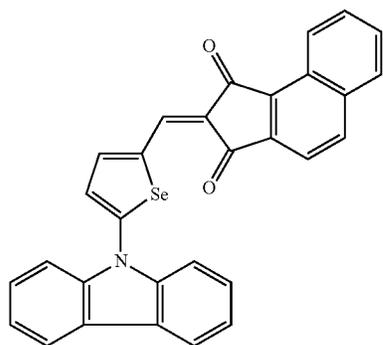
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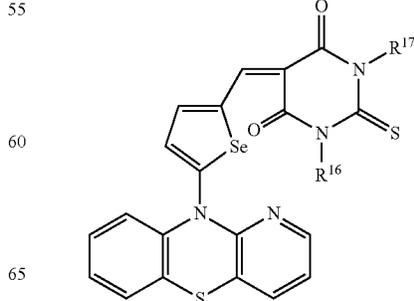
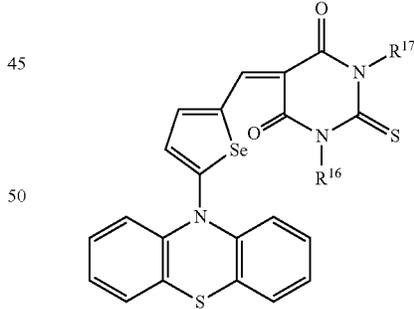
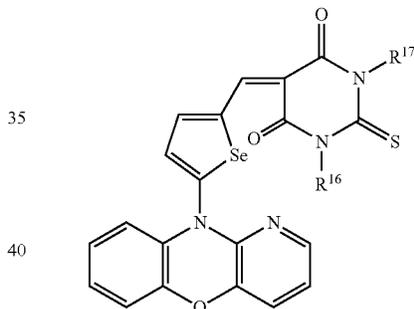
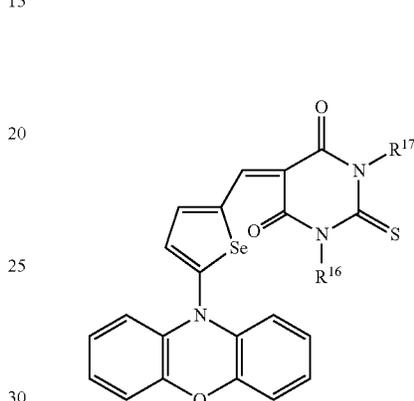
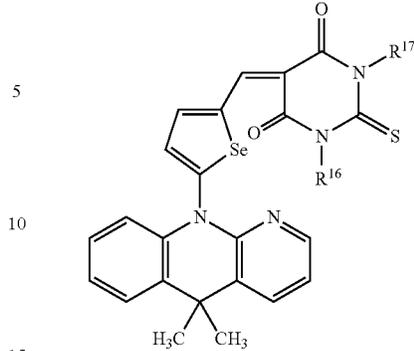
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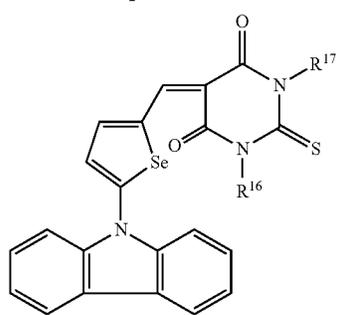
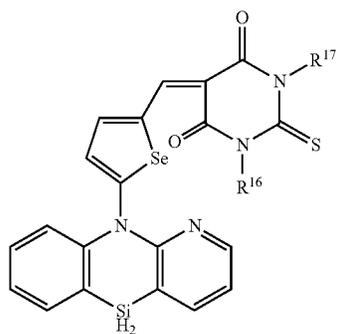
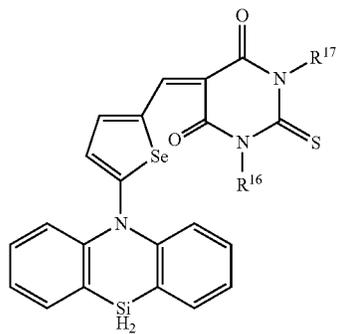
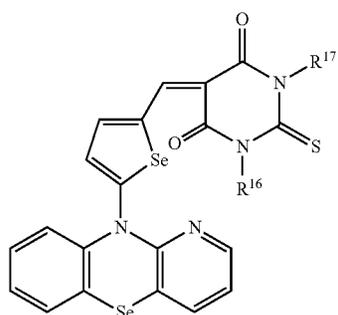
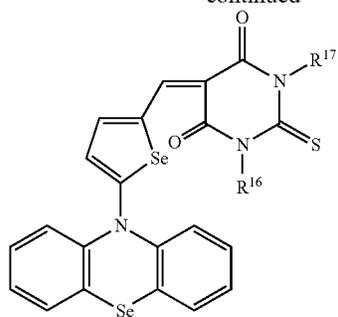
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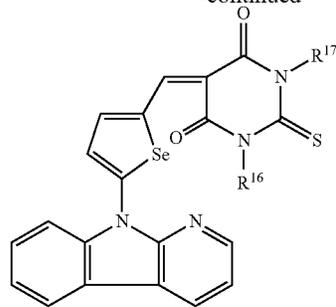
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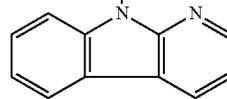
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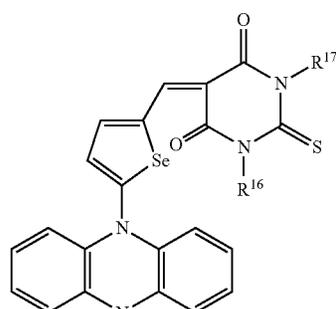


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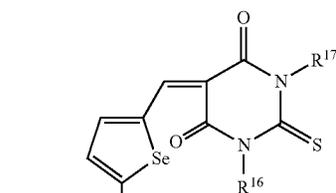
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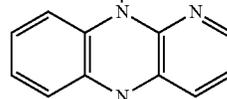


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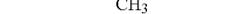
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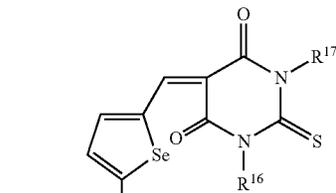
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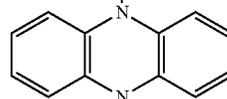
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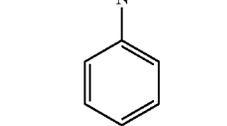
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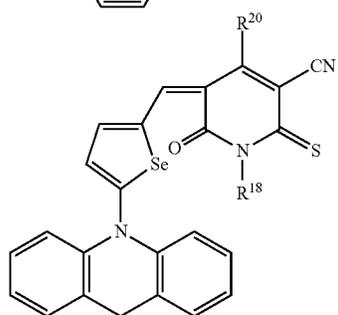
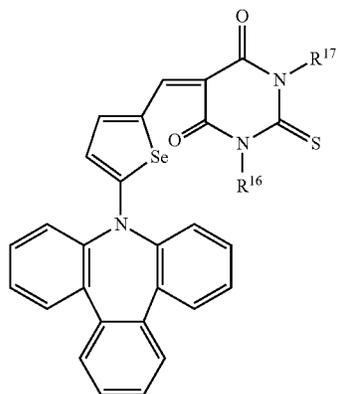
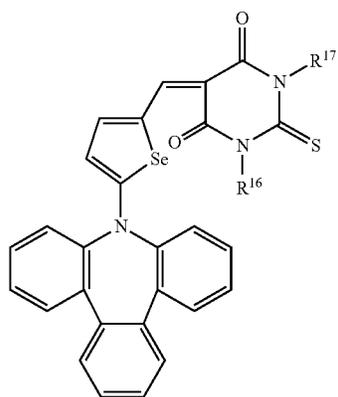
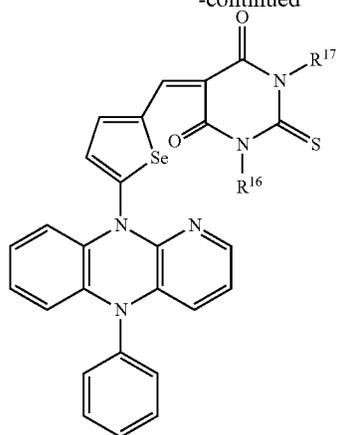


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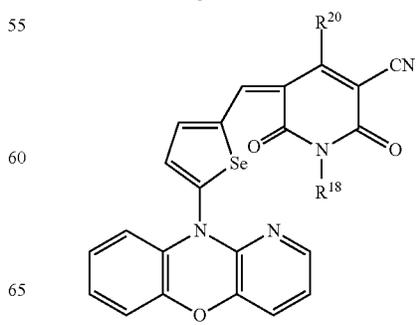
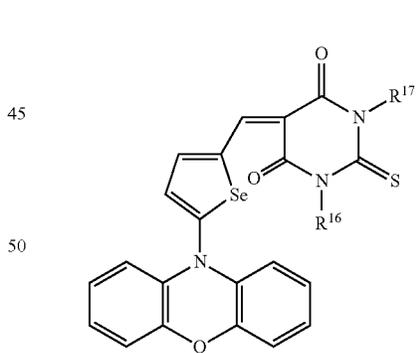
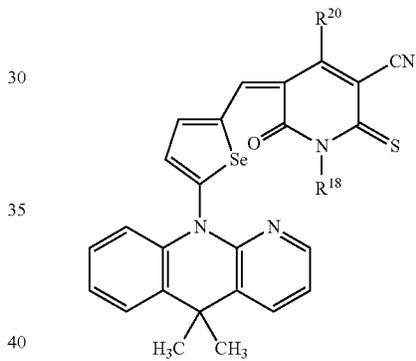
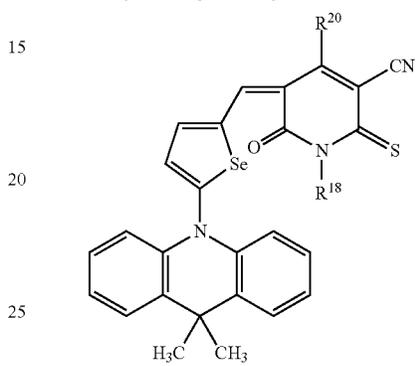
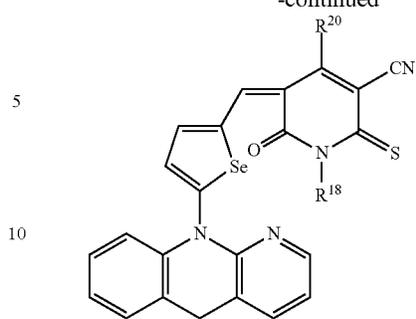
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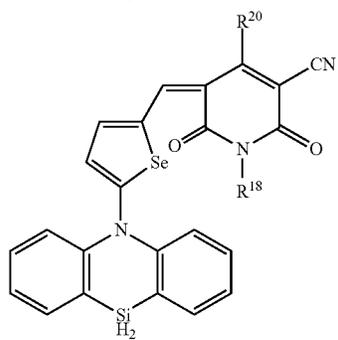
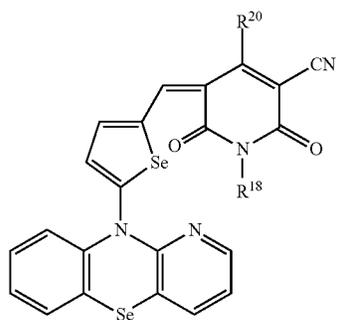
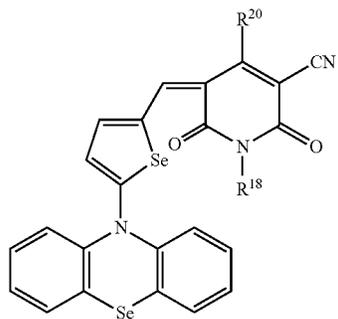
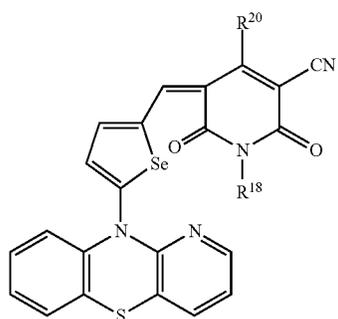
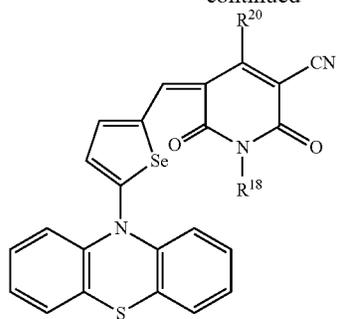
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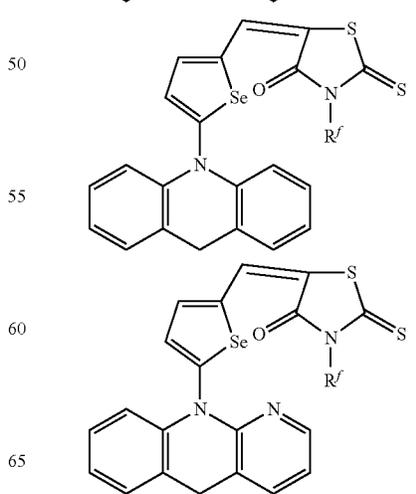
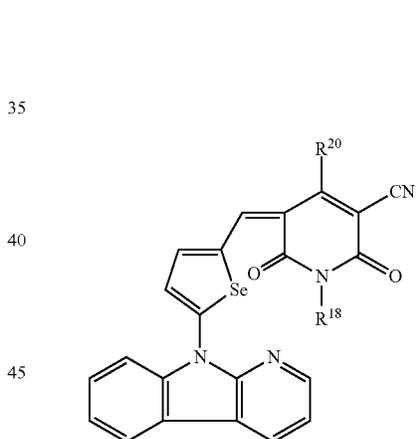
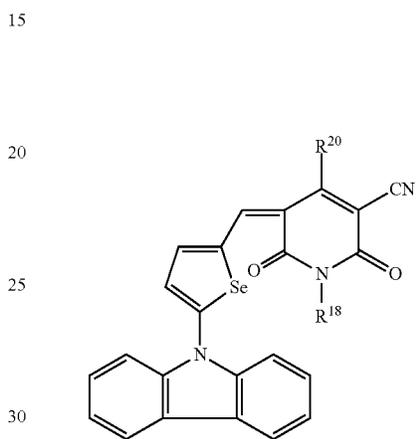
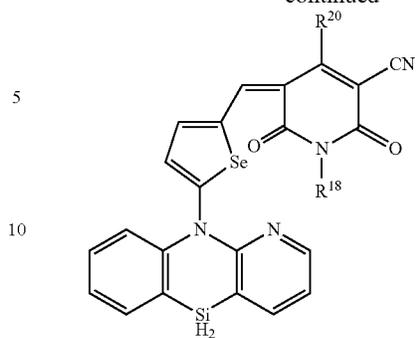
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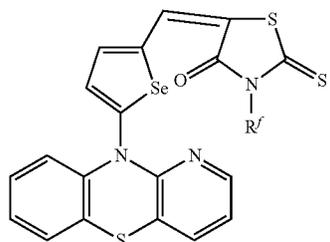
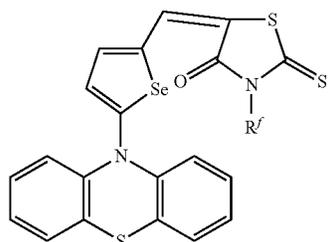
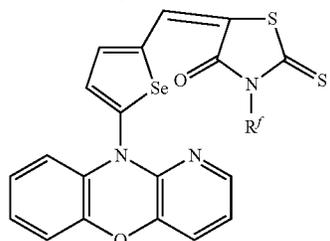
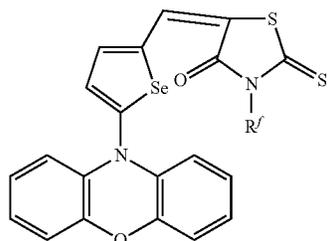
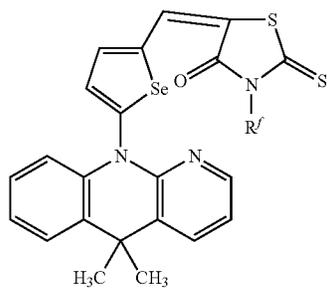
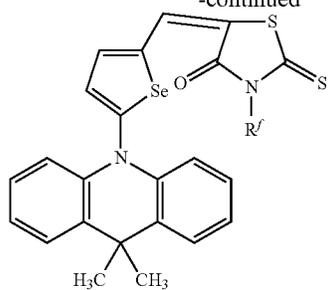
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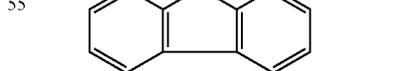
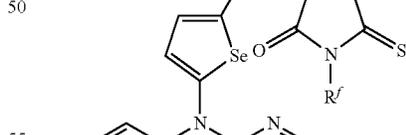
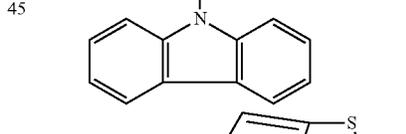
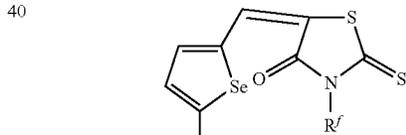
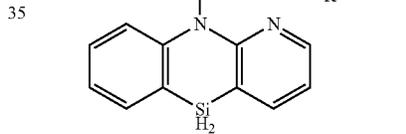
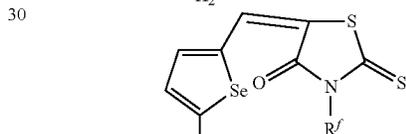
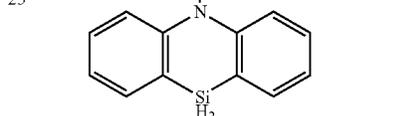
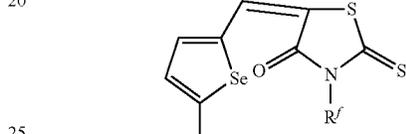
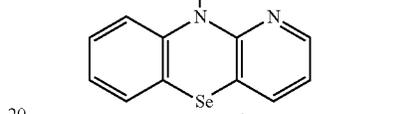
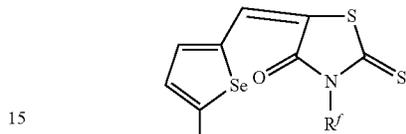
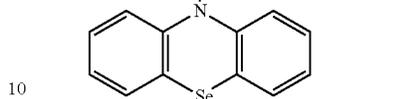
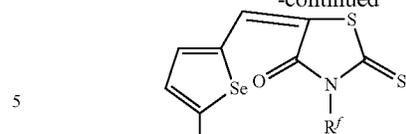
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60 In Group 2,
 hydrogen of each aromatic ring may be replaced by a
 substituted selected from a substituted or unsubstituted C₁ to
 C₃₀ alkyl group, a substituted or unsubstituted C₁ to C₃₀
 alkoxy group, a substituted or unsubstituted C₆ to C₃₀ aryl
 group, a substituted or unsubstituted C₄ to C₃₀ heteroaryl
 group, a halogen, a cyano group, a cyano-containing group,
 65 and a combination thereof, and

each of R¹⁶, R¹⁷, R¹⁸, R²⁰, and R^f are independently hydrogen, a substituted or unsubstituted C₁ to C₃₀ alkyl group, a substituted or unsubstituted C₁ to C₃₀ alkoxy group, a substituted or unsubstituted Ce to C₃₀ aryl group, a substituted or unsubstituted C₄ to C₃₀ heteroaryl group, halogen, a cyano group, a cyano-containing group, or a combination thereof.

The light-absorption layer **30** may be an intrinsic layer (1 layer), and may further include a p-type layer and/or an n-type layer on one surface or both surfaces of the light-absorption layer **30**. For example, the organic photoelectronic device **100** may include various combinations of a p-type layer/l layer, an l layer/n-type layer, a p-type layer/l layer/n-type layer, etc., between the first electrode **10** and the second electrode **20**. The p-type layer may include a p-type light-absorbing material and the n-type layer may include an n-type light-absorbing material.

The light-absorption layer **30** may have a thickness of about 1 nm to about 500 nm, and specifically, about 5 nm to about 300 nm. When the light-absorption layer **30** has a thickness within the range, the light-absorption layer **30** may effectively absorb light, effectively separate holes from electrons, and deliver them, thereby effectively improving photoelectronic conversion efficiency.

The organic photoelectronic device **100** may further include an anti-reflection layer (not shown) on one surface of the first electrode **10** or the second electrode **20**.

The anti-reflection layer is disposed at an incident side and may lower reflectance of incident light and further improve light absorption. For example, when light enters the first electrode **10**, the anti-reflection layer may be disposed on one surface of the first electrode **10**, and when light enters the second electrode **20**, the anti-reflection layer may be disposed on one surface of the second electrode **20**.

The anti-reflection layer may for example include a material having a refractive index of about 1.6 to about 2.5, for example, at least one of a metal oxide, a metal sulfide, and an organic material having a refractive index within the range. The anti-reflection layer may for example include a metal oxide such as an aluminum-containing oxide, a molybdenum-containing oxide, a tungsten-containing oxide, a vanadium-containing oxide, a rhenium-containing oxide, a niobium-containing oxide, a tantalum-containing oxide, a titanium-containing oxide, a nickel-containing oxide, a copper-containing oxide, a cobalt-containing oxide, a manganese-containing oxide, a chromium-containing oxide, a tellurium-containing oxide, or a combination thereof; a metal sulfide such as a zinc sulfide; or an organic material such as an amine derivative but is not limited thereto.

FIG. 3 is a cross-sectional view showing an organic photoelectronic device according to example embodiments.

Referring to FIG. 3, an organic photoelectronic device **200** according to example embodiments includes a first electrode **10** and a second electrode **20** facing each other, and the light-absorption layer **30** between the first electrode **10** and the second electrode **20**, like the above example embodiment illustrated in FIG. 2. The first electrode **10**, the second electrode **20**, and the light-absorption layer **30** are the same as described above.

However, the organic photoelectronic device **200** according to example embodiments further includes charge auxiliary layers **40** and **50** between the first electrode **10** and the light-absorption layer **30** and the second electrode **20** and the light-absorption layer **30**, unlike the above example embodiment illustrated in FIG. 2. The charge auxiliary layers **40** and

50 may facilitate the transfer of holes and electrons separated from the light-absorption layer **30**, so as to increase efficiency.

The charge auxiliary layers **40** and **50** may be at least one selected from a hole injection layer (HIL) for facilitating hole injection, a hole transport layer (HTL) for facilitating hole transport, an electron blocking layer (EBL) for reducing or preventing electron transport, an electron injection layer (EIL) for facilitating electron injection, an electron transport layer (ETL) for facilitating electron transport, and a hole blocking layer (HBL) for reducing or preventing hole transport.

The charge auxiliary layers **40** and **50** may include, for example, an organic material, an inorganic material, or an organic/inorganic material. The organic material may be an organic compound having hole or electron characteristics, and the inorganic material may be, for example, a metal oxide such as a molybdenum oxide, a tungsten oxide, a nickel oxide, etc.

The hole transport layer (HTL) may include one selected from, for example, poly(3,4-ethylenedioxythiophene):poly(styrenesulfonate) (PEDOT:PSS), polyarylamine, poly(N-vinylcarbazole), polyaniline, polypyrrole, N,N,N',N'-tetrakis(4-methoxyphenyl)-benzidine (TPD), 4-bis[N-(1-naphthyl)-N-phenyl-amino]biphenyl (α -NPD), m-MTDATA, 4,4',4"-tris(N-carbazolyl)-triphenylamine (TCTA), and a combination thereof, but is not limited thereto.

The electron blocking layer (EBL) may include one selected from, for example, poly(3,4-ethylenedioxythiophene):poly(styrenesulfonate) (PEDOT:PSS), polyarylamine, poly(N-vinylcarbazole), polyaniline, polypyrrole, N,N,N',N'-tetrakis(4-methoxyphenyl)-benzidine (TPD), 4-bis[N-(1-naphthyl)-N-phenyl-amino]biphenyl (α -NPD), m-MTDATA, 4,4',4"-tris(N-carbazolyl)-triphenylamine (TCTA), and a combination thereof, but is not limited thereto.

The electron transport layer (ETL) may include one selected from, for example, 1,4,5,8-naphthalene-tetracarboxylic dianhydride (NTCDA), bathocuproine (BCP), LiF, Alq₃, Gaq₃, Inq₃, Znq₂, Zn(BTZ)₂, BeBq₂, and a combination thereof, but is not limited thereto.

The hole blocking layer (HBL) may include one selected from, for example, 1,4,5,8-naphthalene-tetracarboxylic dianhydride (NTCDA), bathocuproine (BCP), LiF, Alq₃, Gaq₃, Inq₃, Znq₂, Zn(BTZ)₂, BeBq₂, and a combination thereof, but is not limited thereto.

Either one of the charge auxiliary layers **40** and **50** may be omitted.

The organic photoelectronic device may be applied to an image sensor, a photo-detector, a photo-sensor, etc., but is not limited thereto.

The organic photoelectronic device may be for example applied to an image sensor.

Hereinafter, an example of an image sensor including the organic photoelectronic device is described referring to drawings. As an example of an image sensor, an organic CMOS image sensor is illustrated.

FIG. 4 is a schematic top plan view showing an organic CMOS image sensor according to example embodiments. FIG. 5A is a cross-sectional view showing one example of the organic CMOS image sensor of FIG. 4 and FIG. 5B is a cross-sectional view of a portion A of the image sensor **300** illustrated in FIG. 5A.

Referring to FIGS. 4, 5A and 5B, an organic CMOS image sensor **300** according to example embodiments includes a semiconductor substrate **110** integrated with photo-sensing

51

devices **50B** and **50R**, a transmission transistor **90**, and a charge storage **55**, a lower insulation layer **60**, a color filter layer **70**, an upper insulation layer **80**, and an organic photoelectronic device **100**.

The semiconductor substrate **110** may be a silicon substrate, and is integrated with the photo-sensing devices **50B** and **50R**, the transmission transistor (not shown), and the charge storage **55**. The photo-sensing devices **50R** and **50B** may be photodiodes.

The photo-sensing devices **50B** and **50R**, the transmission transistor **90**, and/or the charge storage **55** may be integrated in each pixel, and as shown in the drawing, the photo-sensing devices **50B** and **50R** may be included in a blue pixel and a red pixel and the charge storage **55** may be included in a green pixel.

The photo-sensing devices **50B** and **50R** sense light, the information sensed by the photo-sensing devices may be transferred by the transmission transistor **90**, and the charge storage **55** is electrically connected with the organic photoelectronic device **100**, so the information of the charge storage **55** may be transferred by the transmission transistor **90**.

In some example embodiments, including the example embodiments shown in FIG. **5B**, a metal wire **62** and a pad **64** are formed on the semiconductor substrate **110**. In order to decrease signal delay, the metal wire **62** and pad **64** may at least partially comprise a metal having relatively low resistivity, for example, aluminum (Al), copper (Cu), silver (Ag), and alloys thereof, but is not limited thereto. In some example embodiments, the metal wire **62** and pad **64** may be positioned under the photo-sensing devices **50B** and **50R**.

Referring back to FIG. **5A**, the lower insulation layer **60** is formed on the metal wire **62** and the pad **64**. The lower insulation layer **60** may at least partially comprise an inorganic insulating material including a silicon oxide and/or a silicon nitride, or a low dielectric constant (low K) material including SiC, SiCOH, SiCO, and SiOF. The lower insulation layer **60** has a through-hole **85** exposing the charge storage **55**. The through-hole **85** may be filled with fillers.

A color filter layer **70** is formed on the lower insulation layer **60**. The color filter layer **70** includes a blue filter **70B** formed in the blue pixel and a red filter **70R** formed in the red pixel. In example embodiments, a green filter is not formed but may be formed if needed.

The upper insulation layer **80** is formed on the color filter layer **70**. The upper insulation layer **80** eliminates a step caused by the color filter layer **70** and smoothes the surface. The upper insulation layer **80** and lower insulation layer **60** may include a contact hole (not shown) exposing a pad, and the through-hole **85** exposing the charge storage **55** of a green pixel.

The organic photoelectronic device **100** is formed on the upper insulation layer **80**. The organic photoelectronic device **100** includes the first electrode **10**, the light-absorption layer **30**, and the second electrode **20** as described above.

The first electrode **10** and the second electrode **20** may be transparent electrodes, and the light-absorption layer **30** is the same as described above. The light-absorption layer **30** may selectively absorb light in a green wavelength region and replaces a color filter of a green pixel.

When light enters from the second electrode **20**, the light in a green wavelength region may be mainly absorbed in the light-absorption layer **30** and photoelectrically converted, while the light in the rest of the wavelength regions passes through the first electrode **10** and may be sensed in photo-sensing devices **50B** and **50R**.

52

As described above, the organic photoelectronic device configured to selectively absorb light in a green wavelength region has a stack structure, and thus the size of an image sensor may be reduced to realize a down-sized image sensor. In addition, as described above, a crosstalk due to light in other wavelength regions except green may be reduced and sensitivity of an image sensor may be increased by improving green wavelength selectivity in the light-absorption layer **30** of the organic photoelectronic device **100**.

In FIG. **5A**, the organic photoelectronic device **100** of FIG. **1** is included, but it is not limited thereto, and thus the organic photoelectronic device **200** of FIG. **3** may be applied in the same manner.

In FIGS. **4** and **5A**, a stack structure where an organic photoelectronic device configured to selectively absorb light in a green wavelength region is stacked is illustrated as an example, but the present disclosure is not limited thereto. The present disclosure may have a structure where an organic photoelectronic device configured to selectively absorb light in a blue wavelength region is stacked and a green photo-sensing device and a red photo-sensing device may be integrated in the semiconductor substrate **110**, or a structure where an organic photoelectronic device configured to selectively absorb light in a red wavelength region is stacked and a green photo-sensing device and a blue photo-sensing device may be integrated in the semiconductor substrate **110**.

FIG. **6** is a cross-sectional view showing another example of the organic CMOS image sensor of FIG. **4**.

The organic CMOS image sensor **400** according to example embodiments includes a semiconductor substrate **110** integrated with photo-sensing devices **50B** and **50R**, a transmission transistor (not shown), and a charge storage **55**, an upper insulation layer **80**, and an organic photoelectronic device **100**, like the above example embodiment illustrated in FIG. **5A**.

The organic CMOS image sensor **400** according to example embodiments includes the blue photo-sensing device **50B** and the red photo-sensing device **50R** stacked in a vertical direction and a color filter layer **70** is omitted. The blue photo-sensing device **50B** and the red photo-sensing device **50R** are electrically connected with the charge storage **55** and may be transferred by the transmission transistor **90**.

The blue photo-sensing device **50B** and the red photo-sensing device **50R** may selectively absorb light in each wavelength region according to a stack depth.

As described above, the organic photoelectronic device configured to selectively absorb light in a green wavelength region has a stack structure and the red photo-sensing device and the blue photo-sensing device are stacked and thus the size of an image sensor may be reduced to realize a down-sized image sensor. In addition, as described above, a crosstalk due to light in other wavelength regions except green may be reduced and sensitivity may be increased by improving green wavelength selectivity in the light-absorption layer **30** of the organic photoelectronic device **100**.

In FIG. **6**, the organic photoelectronic device **100** of FIG. **1** is included, but it is not limited thereto, and thus the organic photoelectronic device **200** of FIG. **3** may be applied in the same manner.

In FIG. **6**, a stack structure where an organic photoelectronic device configured to selectively absorb light in a green wavelength region is stacked is exemplarily illustrated, but the present disclosure is not limited thereto. The present disclosure may have a structure where an organic photoelectronic device configured to selectively absorb light

in a blue wavelength region is stacked and a green photo-sensing device and a red photo-sensing device may be integrated in the semiconductor substrate **110**, or a structure where an organic photoelectronic device configured to selectively absorb light in a red wavelength region is stacked and a green photo-sensing device and a blue photo-sensing device may be integrated in the semiconductor substrate **110**.

FIG. 7 is a schematic top plan view showing an organic CMOS image sensor according to example embodiments, and FIG. 8A is a cross-sectional view of an organic CMOS image sensor of FIG. 7 and FIG. 8B is a cross-sectional view of a portion A of the image sensor **500** illustrated in FIG. 8A.

The organic CMOS image sensor **500** according to example embodiments includes a green photoelectronic device configured to selectively absorb light in a green wavelength region, a blue photoelectronic device configured to selectively absorb light in a blue wavelength region, and a red photoelectronic device configured to selectively absorb light in a red wavelength region, and they are stacked.

The organic CMOS image sensor **500** according to example embodiments includes a semiconductor substrate **110**, a lower insulation layer **60**, an intermediate insulation layer **70**, an upper insulation layer **80**, a first organic photoelectronic device **100a**, a second organic photoelectronic device **100b**, and a third organic photoelectronic device **100c**.

The semiconductor substrate **110** may be a silicon substrate, and is integrated with the transmission transistor **90** and the charge storages **55a**, **55b**, and **55c**.

In some example embodiments, including the example embodiments shown in FIG. 9B, a metal wire **62** and a pad **64** are formed on the semiconductor substrate **110**, and the lower insulation layer **60** is formed on the metal wire **62** and the pad **64**.

The first organic photoelectronic device **100a** is formed on the lower insulation layer **60**.

The first organic photoelectronic device **100a** includes a first electrode **10a** and a second electrode **20a** facing each other and a light-absorption layer **30a** between the first electrode **10a** and the second electrode **20a**. One of the first electrode **10a** and the second electrode **20a** may be an anode and the other may be a cathode. The light-absorption layer **30a** may selectively absorb light in one of red, blue, and green wavelength regions. For example, the first organic photoelectronic device **100a** may be a red photoelectronic device.

The second organic photoelectronic device **100b** is formed on the intermediate insulation layer **70**.

The second organic photoelectronic device **100b** is formed on the intermediate insulation layer **70**.

The second organic photoelectronic device **100b** includes a first electrode **10b** and a second electrode **20b** facing each other and a light-absorption layer **30b** between the first electrode **10b** and the second electrode **20b**. One of the first electrode **10b** and the second electrode **20b** may be an anode and the other may be a cathode. The light-absorption layer **30b** may selectively absorb light in one of red, blue, and green wavelength regions. For example, the second organic photoelectronic device **100b** may be a blue photoelectronic device.

The upper insulation layer **80** is formed on the second organic photoelectronic device **100b**. The lower insulation layer **60**, the intermediate insulation layer **70**, and the upper insulation layer **80** have a plurality of through-holes exposing the charge storages **55a**, **55b**, and **55c**.

The third organic photoelectronic device **100c** is formed on the upper insulation layer **80**. The third organic photoelectronic device **100c** includes a first electrode **10c** and a second electrode **20c** and the light-absorption layer **30c** between the first electrode **10c** and the second electrode **20c**. One of the first electrode **10c** and the second electrode **20c** may be an anode and the other may be a cathode. The light-absorption layer **30c** may selectively absorb light in one of red, blue, and green wavelength regions. For example, the third organic photoelectronic device **100c** may be a green photoelectronic device.

At least one of the light-absorption layer **30a** of the first organic photoelectronic device **100a**, the light-absorption layer **30b** of the second organic photoelectronic device **100b**, and the light-absorption layer **30c** of the third organic photoelectronic device **100c** a photoelectric conversion region and a doped region including an exciton quencher, as described above. Specific illustration is the same as described above.

The drawing shows a structure in which the first organic photoelectronic device **100a**, the second organic photoelectronic device **100b**, and the third organic photoelectronic device **100c** are sequentially stacked, but the present disclosure is not limited thereto, and they may be stacked in various orders.

As described above, the first organic photoelectronic device **100a**, the second organic photoelectronic device **100b**, and the third organic photoelectronic device **100c** have a stack structure, and thus the size of an image sensor may be reduced to realize a down-sized image sensor. In addition, as described above, a crosstalk due to light in other wavelength regions except green may be reduced and sensitivity may be increased by improving green wavelength selectivity in the light-absorption layer **30** of the organic photoelectronic device **100**.

The image sensor may be applied to, for example, various electronic devices such as a mobile phone or a digital camera, but is not limited thereto.

FIG. 9 is a diagram illustrating an electronic device **600** according to some example embodiments.

Referring to FIG. 9, the electronic device **600** includes a memory **620**, a processor **630**, an image sensor **640**, and a communication interface **650**. The image sensor **640** may include any of the image sensors illustrated and described herein, including image sensor **300** shown in FIGS. 4 and 5A-5B and image sensor **400** shown in FIGS. 7 and 8A-8B.

The electronic device **600** may be included in one or more various electronic devices, including, for example, a mobile phone, a digital camera, etc. In example embodiments, the electronic device **600** may include one or more of an image providing server, a mobile device, a computing device, an image outputting device, and an image capturing device. A mobile device may include a mobile phone, a smartphone, a personal digital assistant (PDA), some combination thereof, etc. A computing device may include a personal computer (PC), a tablet computer, a laptop computer, a netbook, some combination thereof, etc. An image outputting device may include a TV, a smart TV, some combination thereof, etc. An image capturing device may include a camera, a camcorder, some combination thereof, etc.

The memory **620**, the processor **630**, the image sensor **640**, and the communication interface **650** may communicate with one another through a bus **610**.

The communication interface **650** may communicate data from an external device using various Internet protocols. For example, the communication interface **650** may communicate sensor data generated by the image sensor **640** to an

external device. The external device may include, for example, an image providing server, a display device, a mobile device including, a mobile phone, a smartphone, a personal digital assistant (PDA), a tablet computer, and a laptop computer, a computing device including a personal computer (PC), a tablet PC, and a netbook, an image outputting device including a TV and a smart TV, and an image capturing device including a camera and a camcorder.

The processor **630** may execute a program and control the electronic device **600**. A program code to be executed by the processor **630** may be stored in the memory **620**. An electronic system may be connected to an external device through an input/output device (not shown) and exchange data with the external device.

The memory **620** may store information output from the image sensor **640**, including information transmitted from the transistor **90**. The memory **620** may be a volatile or a nonvolatile memory. The memory **620** may be a non-transitory computer readable storage medium. The memory may store computer-readable instructions that, when executed, cause the execution of one or more methods, functions, processes, etc. as described herein. In some example embodiments, the processor **630** may execute one or more of the computer-readable instructions stored at the memory **620**.

In some example embodiments, the electronic device may include a display panel **660** that may output an image generated based at least in part upon information output from the image sensor **640**.

In some example embodiments, element **660** may be absent from the electronic device **600**. In some example embodiments, the communication interface **650** may include a USB and/or HDMI interface. In some example embodiments, the communication interface **650** may include a wireless communication interface.

FIG. **10** is a cross-sectional view showing a solar cell **1100** according to some example embodiments. Referring to FIG. **10**, a solar cell **1100** includes a first electrode **1102** and a second electrode **1110**, and a photoactive layer **1106** positioned between the first electrode **1102** and the second electrode **1110**.

A substrate (not shown) may be positioned at the first electrode **1102** or the second electrode **1110**, and may include a light-transmitting material. The light-transmitting material may include, for example, an inorganic material (e.g., glass), or an organic material (e.g., polycarbonate, polymethylmethacrylate, polyethylene terephthalate, polyethylene naphthalate, polyamide, polyethersulfone, or a combination thereof).

One of the first electrode **1102** and the second electrode **1110** is an anode and the other is a cathode. At least one of the first electrode **1102** and second electrode **1110** may be a light-transmitting electrode, and light may enter toward the light-transmitting electrode. The light-transmitting electrode may be made of, for example, a conductive oxide (e.g., indium tin oxide (ITO)), indium doped zinc oxide (IZO), tin oxide (SnO₂), aluminum-doped zinc oxide (AZO), and/or gallium-doped zinc oxide (GZO), or a transparent conductor of a conductive carbon composite (e.g., carbon nanotubes (CNT) or graphenes). At least one of the first electrode **1102** and the second electrode **1110** may be an opaque electrode, which may be made of an opaque conductor, for example, aluminum (Al), silver (Ag), gold (Au), and/or lithium (Li).

The photoactive layer **1106** may include an organic photoelectronic device according to some example embodiments.

First and second auxiliary layers **1104** and **1108** may be positioned between the first electrode **1102** and the photoactive layer **1106** and between the second electrode **1110** and the photoactive layer **1106**, respectively. The first and second auxiliary layers **1104** and **1108** may increase charge mobility between the first electrode **1102** and the photoactive layer **1106** and between the second electrode **1110** and the photoactive layer **1106**. The first and second auxiliary layers **1104** and **1106** may be at least one selected from, for example, an electron injection layer (EIL), an electron transport layer, a hole injection layer (HIL), a hole transport layer, and a hole blocking layer, but are not limited thereto. One or both of the first and second auxiliary layers **1104** and **1108** may be omitted.

The photoactive layer **1106** may have a tandem structure where at least two thereof are stacked.

FIG. **11** is a sectional view of an organic light-emitting display apparatus **1200** according to some example embodiments.

Referring to FIG. **11**, a first electrode **1203a** and a second electrode **1203b** are positioned on a substrate **1201**, a first emission layer **1205a** is positioned on the first electrode **1203a**, and a second emission layer **1205b** is positioned under the second electrode **1203b**.

The substrate **1201** may include a material selected from the group consisting of glass, quartz, silicon, a synthetic resin, a metal, and a combination thereof. The synthetic resin may include polyethylene naphthalate (PEN), polyethylene terephthalate (PET), polycarbonate, polyvinyl alcohol, polyacrylate, polyimide, polynorbornene and/or polyethersulfone (PES), etc. The metal plate may include a stainless steel foil and/or an aluminum foil, etc.

The first electrode **1203a** may include a material having a work function of about 4.3 eV to about 5.0 eV, about 4.3 eV to about 4.7 eV, or about 4.3 eV to about 4.5 eV. According to example embodiments, the material may include aluminum (Al), copper (Cu), magnesium (Mg), molybdenum (Mo) and/or an alloy thereof, etc. In addition, these metals may be laminated to provide a first electrode. The first electrode **1203a** may have a thickness of about 120 to about 120 nm.

The second electrode **1203b** may include a material having a work function of about 12.3 eV to about 12.7 eV or about 12.5 eV to about 12.7 eV. According to some example embodiments, the second electrode **1203b** may include Ba:Al. The second electrode **1203b** may have a thickness of about 120 to about 120 nm.

The first emission layer **1205a** and the second emission layer **1205b** may include an organic photoelectronic device according to some example embodiments.

A middle electrode **1209** is positioned between the first emission layer **1205a** and the second emission layer **1205b**. The middle electrode **1209** may include a material having a work function of about 5.0 eV to about 5.2 eV. According to some example embodiments, the material may include a conductive polymer. The conductive polymer may include polythiophene, polyaniline, polypyrrole, polyacene, polyphenylene, polyphenylenevinylene, a derivative thereof, a copolymer thereof, or a mixture thereof.

A buffer layer **1207** may be positioned between the first emission layer **1205a** and the middle electrode **1209**, and may include a material selected from the group consisting of a metal oxide, a polyelectrolyte, and combinations thereof. The combination thereof refers to the metal oxide and polyelectrolyte being mixed or laminated to provide a multilayer. In addition, the different kinds of metal oxide or polyelectrolyte may be laminated.

57

FIG. 12 is a view showing a sensor 1300 according to some example embodiments.

Referring to FIG. 12, a sensor 1300 (for example a gas sensor, light sensor, energy sensor, but example embodiments are not limited thereto) includes at least one electrode 1320 configured to output a signal to a processor 1330. The processor 1330 may include a microprocessor, but example embodiments are not limited thereto. The electrode 1320 may include an organic photoelectronic device according to some example embodiments.

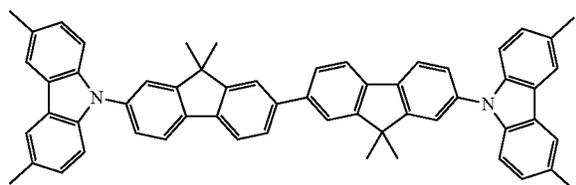
Hereinafter, the present disclosure is illustrated in more detail with reference to examples. However, these examples are exemplary, and the present disclosure is not limited thereto.

Manufacture of Organic Photoelectronic Device I

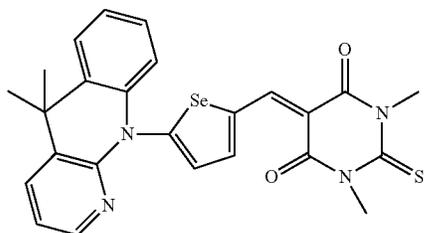
Example 1

An about 150 nm-thick anode is formed by sputtering ITO on a glass substrate. On the anode, a 5 nm-thick lower buffer layer is formed by depositing a compound represented by Chemical Formula A. On the lower buffer layer, a 110 nm-thick light-absorption layer is formed by codepositing a compound represented by Chemical Formula B as a p-type light-absorbing material, C60 as an n-type light-absorbing material and molybdenum oxide (MoO_x, 0 < x ≤ 3). Herein, the light-absorption layer has a 15 nm-thick lower photoelectric conversion region formed by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 2:1, a 20 nm-thick doped region formed by ternary-codepositing the p-type light-absorbing material, the n-type light-absorbing material, and a molybdenum oxide in a volume ratio of 2:1:2 among them, and a 75 nm-thick upper photoelectric conversion region formed by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 2:1. Subsequently, on the light-absorption layer, a 7 nm-thick cathode is formed by sputtering ITO, and a 50 nm-thick high refractive index layer is formed thereon by depositing an aluminum oxide to manufacture an organic photoelectronic device.

[Chemical Formula A]



[Chemical Formula B]



Example 2

An organic photoelectronic device is manufactured according to the same method as Example 1 except for

58

binary-codepositing a p-type light-absorbing material and a n-type light-absorbing material in a volume ratio of 2:1 to form a 30 nm-thick lower photoelectric conversion region, ternary-codepositing the p-type light-absorbing material, the n-type light-absorbing material, and a molybdenum oxide in a volume ratio of 2:1:2 to form a 20 nm-thick doped region, and binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 2:1 to form a 60 nm-thick upper photoelectric conversion region during formation of the light-absorption layer.

Example 3

An organic photoelectronic device is manufactured according to the same method as Example 1 except for binary-codepositing a p-type light-absorbing material and a n-type light-absorbing material in a volume ratio of 2:1 between them to form a 30 nm-thick lower photoelectric conversion region, ternary-codepositing the p-type light-absorbing material, the n-type light-absorbing material, and a molybdenum oxide in a volume ratio of 2:1:1 among them to form a 20 nm-thick doped region, and binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 2:1 between them to form a 60 nm-thick upper photoelectric conversion region during formation of the light-absorption layer.

Example 4

An organic photoelectronic device is manufactured according to the same method as Example 1 except for binary-codepositing a p-type light-absorbing material and a n-type light-absorbing material in a volume ratio of 2:1 between them to form a 45 nm-thick lower photoelectric conversion region, ternary-codepositing the p-type light-absorbing material, the n-type light-absorbing material, and a molybdenum oxide in a volume ratio of 2:1:2 among them to form a 20 nm-thick doped region, and binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 2:1 between them to form a 45 nm-thick upper photoelectric conversion region during formation of the light-absorption layer.

Comparative Example 1

An organic photoelectronic device is manufactured according to the same method as Example 1 except for forming a 110 nm-thick light-absorption layer having a volume ratio of 2:1 by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material.

55 Evaluation I

External quantum efficiency (EQE) of the organic photoelectronic devices of Examples 1 to 4 and Comparative Example 1 depending on a wavelength region is compared.

The external quantum efficiency (EQE) is evaluated in a 400 nm to 720 nm wavelength region ($\lambda_{max}=570$ nm) in an Incident Photon to Current Efficiency (IPCE) method. A green wavelength region has a reference wavelength of about 570 nm as a maximum absorption wavelength (λ_{max}), and a blue wavelength region has a reference wavelength of 450 nm.

The results are provided in Table 1.

59

TABLE 1

	$EQE_{max(G)}$ (%)	$EQE_{450\text{ nm}(B)}$ (%)	$EQE_{max(G)}/$ $EQE_{450\text{ nm}(B)}$	Full width at half maximum (FWHM) (nm)
Example 1	63.9	15.2	4.20	102
Example 2	59.6	11.5	5.17	100
Example 3	58.6	12.1	4.83	97
Example 4	56.9	8.4	6.76	93
Comparative Example 1	66.8	18.2	3.67	110

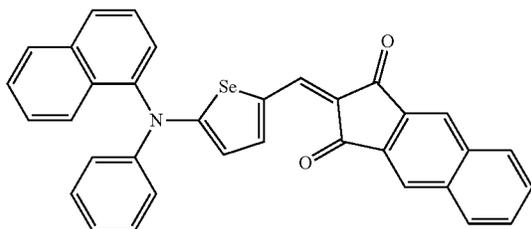
Referring to Table 1, the organic photoelectric devices according to Examples 1 to 4 shows low absorption of blue light and improved wavelength selectivity of green light.

Manufacture of Organic Photoelectric Device II

Example 5

An about 150 nm-thick anode is formed by sputtering by ITO on a glass substrate. On the anode, a 110 nm-thick light-absorption layer is formed by codepositing a compound represented by Chemical Formula C as a p-type light-absorbing material, C60 as an n-type light-absorbing material, and molybdenum oxide (MoOx, 0 < x ≤ 3). Herein, the light-absorption layer has a 30 nm-thick lower photoelectric conversion region formed by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 2:1, a 20 nm-thick doped region formed by ternary-codepositing the p-type light-absorbing material, the n-type light-absorbing material, and a molybdenum oxide in a volume ratio of 2:1:2, and a 60 nm-thick upper photoelectric conversion region formed by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 2:1. Subsequently, on the light-absorption layer, a 10 nm-thick upper buffer layer is formed by depositing MoOx (0 < x ≤ 3):Al (1:1 wt/wt). On the upper buffer layer, a 7 nm-thick cathode is formed by sputtering ITO, and a 50 nm-thick high refractive layer is formed thereon by depositing an aluminum oxide as a high refractive film to manufacture an organic photoelectric device.

[Chemical Formula C]



Comparative Example 2

An organic photoelectric device is manufactured according to the same method as Example 5 except for forming a 110 nm-thick light-absorption layer having a volume ratio of 2:1 by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material.

60

Evaluation II

External quantum efficiency (EQE) of the organic photoelectric devices according to Example 5 and Comparative Example 2 depending on a wavelength region is compared. The results are shown in Table 2.

TABLE 2

	$EQE_{max(G)}$ (%)	$EQE_{450\text{ nm}(B)}$ (%)	$EQE_{max(G)}/$ $EQE_{450\text{ nm}(B)}$	Full width at half maximum (FWHM) (nm)
Example 5	51.6	9.4	5.49	104
Comparative Example 2	45.3	12.1	3.74	113

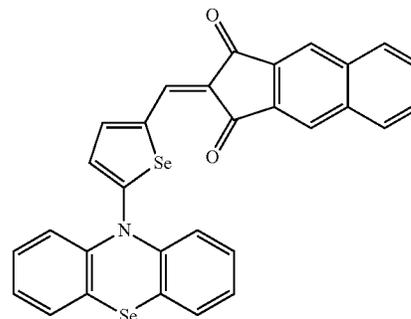
Referring to Table 2, the organic photoelectric device of Example 5 absorbs lower blue light and thus shows improved wavelength selectivity of green light.

Manufacture of Organic Photoelectric Device III

Example 6

An about 150 nm-thick anode is formed by sputtering ITO on a glass substrate. On the anode, a 5 nm-thick lower buffer layer is formed by depositing a compound represented by Chemical Formula A. On the lower buffer layer, a 110 nm-thick light-absorption layer is formed by codepositing a compound represented by Chemical Formula D as a p-type light-absorbing material, C60 as a n-type light-absorbing material, and molybdenum oxide (MoOx, 0 < x ≤ 3). Herein, the light-absorption layer has a 30 nm-thick lower photoelectric conversion region formed by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 1.5:1, a 20 nm-thick doped region formed by ternary-codepositing the p-type light-absorbing material, the n-type light-absorbing material, and the molybdenum oxide in a volume ratio of 1.5:1:1.5, and a 60 nm-thick upper photoelectric conversion region formed by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 1.5:1. On the light-absorption layer, a 7 nm-thick cathode is formed by sputtering ITO, and a 50 nm-thick high refractive layer is formed by depositing an aluminum oxide thereon to manufacture an organic photoelectric device.

[Chemical Formula D]



Example 7

An organic photoelectric device is manufactured according to the same method as Example 6 except for forming 20 nm-thick lower photoelectric conversion region by binary-codepositing a p-type light-absorbing material and a n-type light-absorbing material in a volume ratio of 2:1

between them to form a 45 nm-thick lower photoelectric conversion region, ternary-codepositing the p-type light-absorbing material, the n-type light-absorbing material, and a molybdenum oxide in a volume ratio of 2:1:2 among them to form a 20 nm-thick doped region, and binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material in a volume ratio of 2:1 between them to form a 70 nm-thick upper photoelectric conversion region during formation of the light-absorption layer.

Comparative Example 3

An organic photoelectronic device is manufactured according to the same method as Example 6 except for forming a 110 nm-thick light-absorption layer having a volume ratio of 1.5:1 by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material.

Comparative Example 4

An organic photoelectronic device is manufactured according to the same method as Example 6 except for forming a 110 nm-thick light-absorption layer having a volume ratio of 2:1 by binary-codepositing the p-type light-absorbing material and the n-type light-absorbing material.

External quantum efficiency (EQE) of each organic photoelectronic device according to Example 6 and Comparative Example 3 depending on a wavelength region is compared. Likewise, external quantum efficiency of the organic photoelectronic devices according to Example 7 and Comparative Example 4 depending on a wavelength region is compared.

The results are shown in Tables 3 and 4.

TABLE 3

	EQE _{max(G)} (%)	EQE _{450 nm(B)} (%)	EQE _{max(G)/EQE_{450 nm(B)}}	Full width at half maximum (FWHM) (nm)
Example 6	60.1	15.0	4.00	107
Comparative Example 3	59.5	20.7	2.87	127

TABLE 4

	EQE _{max(G)} (%)	EQE _{450 nm(B)} (%)	EQE _{max(G)/EQE_{450 nm(B)}}	Full width at half maximum (FWHM) (nm)
Example 7	53.6	13.9	3.86	112
Comparative Example 4	45.7	15.8	2.89	131

Referring to Tables 3 and 4, the organic photoelectronic devices according to Examples 6 and 7 absorbs low blue light and thus shows improved wavelength selectivity of green light.

While this disclosure has been described in connection with what is presently considered to be practical example embodiments, it is to be understood that the inventive concepts are not limited to the disclosed embodiments, but, on the contrary, is intended to cover various modifications and equivalent arrangements included within the spirit and scope of the appended claims.

What is claimed is:

1. An organic photoelectronic device, comprising:
 - a first electrode and a second electrode facing each other, one of the first electrode and the second electrode being an anode of the organic photoelectronic device and the other being a cathode of the organic photoelectronic device; and
 - a light-absorption layer between the first electrode and the second electrode, the light-absorption layer including,
 - a first photoelectric conversion region nearer to the first electrode, and a second photoelectric conversion region nearer to the second electrode, and
 - a doped region between the first photoelectric conversion region and the second photoelectric conversion region, such that the first photoelectric conversion region, the doped region, and the second photoelectric conversion region are sequentially disposed along a thickness direction of the light-absorption layer,
 wherein each of the first photoelectric conversion region and the second photoelectric conversion region includes a p-type light-absorbing material and an n-type light-absorbing material forming a bulk heterojunction, at least one of the p-type light-absorbing material and the n-type light-absorbing material being configured to selectively absorb a part of visible light, and
 - the doped region includes the p-type light-absorbing material, the n-type light-absorbing material, and an exciton quencher,
 - wherein, in the doped region, the exciton quencher is included in each of the p-type light-absorbing material and the n-type light-absorbing material as a dopant, the exciton quencher includes a metal, a semi-metal, a metal oxide, a semi-metal oxide, or a combination thereof.
2. The organic photoelectronic device of claim 1, wherein the second electrode is nearer to a light incidence side than the first electrode, and
 - a thickness of the second photoelectric conversion region is the same as or larger than a thickness of the first photoelectric conversion region.
3. The organic photoelectronic device of claim 1, wherein the exciton quencher is copper, silver, gold, aluminum, a molybdenum oxide, a tungsten oxide, a vanadium oxide, a rhenium oxide, a nickel oxide, or a combination thereof.
4. The organic photoelectronic device of claim 1, wherein the exciton quencher is included in an amount less than or equal to about 50 volume % based on the amount of the doped region.
5. The organic photoelectronic device of claim 1, wherein at least one of the p-type light-absorbing material and the n-type light-absorbing material selectively absorbs at least one of a wavelength greater than or equal to about 400 nm and less than 500 nm, a wavelength region of about 500 nm to about 600 nm, and a wavelength region of greater than about 600 nm and less than or equal to about 700 nm.
6. The organic photoelectronic device of claim 1, wherein the light-absorption layer absorbs first visible light and second visible light that are different wavelength regions from each other,
 - the first visible light is absorbed at maximum in the first photoelectric conversion region or the second photoelectric conversion region, and
 - the second visible light is absorbed at maximum in the doped region.

63

7. The organic photoelectronic device of claim 6, wherein one of the p-type light-absorbing material and the n-type light-absorbing material selectively absorbs the first visible light, and

the other of the p-type light-absorbing material and the n-type light-absorbing material absorb the first visible light and the second visible light.

8. The organic photoelectronic device of claim 7, wherein the first visible light is in a wavelength region of about 500 nm to about 600 nm, and

the second visible light is in a wavelength of greater than or equal to about 400 nm and less than 500 nm.

9. The organic photoelectronic device of claim 8, wherein external quantum efficiency of the organic photoelectronic device for the first visible light and the second visible light satisfies Relationship Equation 1:

$$EQE_{max}/EQE_{450\text{ nm}} \approx 3.80 \quad [\text{Relationship Equation 1}]$$

wherein, in Relationship Equation 1,

EQE_{max} is external quantum efficiency of the first visible light at a maximum absorption wavelength which is measured using an incident photon to current efficiency (IPCE), and

$EQE_{450\text{ nm}}$ is external quantum efficiency at 450 nm which is measured using an incident photon to current efficiency (IPCE).

10. The organic photoelectronic device of claim 7, wherein

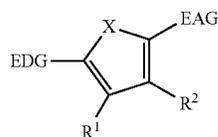
the p-type light-absorbing material selectively absorbs the first visible light, and

the n-type light-absorbing material absorbs the first visible light and the second visible light.

11. The organic photoelectronic device of claim 10, wherein the n-type light-absorbing material is fullerene or a fullerene derivative.

12. The organic photoelectronic device of claim 10, wherein the p-type light-absorbing material is an organic material including a core structure including an electron donating moiety, a pi conjugation linking group, and an electron accepting moiety.

13. The organic photoelectronic device of claim 12, wherein the p-type light-absorbing material is a compound represented by Chemical Formula 1:



[Chemical Formula 1]

wherein, in Chemical Formula 1,

X is Se, Te, SO, SO₂, or SiR^aR^b,

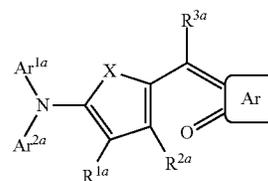
EDG is an electron donating group,

EAG is an electron accepting group, and

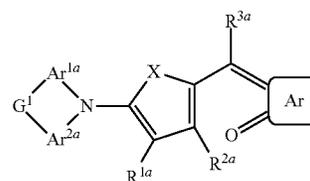
each of R¹, R², R^a, and R^b are independently hydrogen or a monovalent substituent.

64

14. The organic photoelectronic device of claim 13, wherein the p-type light-absorbing material is a compound represented by Chemical Formula 1A or 1B:



[Chemical Formula 1A]



[Chemical Formula 1B]

wherein, in Chemical Formula 1A or 1B,

X is Se, Te, SO, SO₂, or SiR^aR^b,

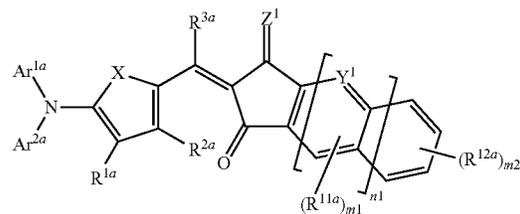
Ar is a substituted or unsubstituted 5-membered ring, a substituted or unsubstituted 6-membered ring, or a condensed ring of the two or more foregoing rings,

each of Ar^{1a} and Ar^{2a} are independently a substituted or unsubstituted C₆ to C₃₀ aryl group or a substituted or unsubstituted C₃ to C₃₀ heteroaryl group,

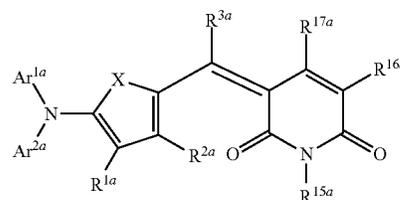
G¹ is selected from a single bond, —(CR^gR^h)_{n2}—, —O—, —S—, —Se—, —N=, —NRⁱ—, —SiR^jR^k—, and —GeR^lR^m—, wherein n2 is 1 or 2, and

each of R^{1a} to R^{3a}, R^a, and R^b are independently hydrogen, a substituted or unsubstituted C₁ to C₃₀ alkyl group, a substituted or unsubstituted C₆ to C₃₀ aryl group, a substituted or unsubstituted C₃ to C₃₀ heteroaryl group, a substituted or unsubstituted C₁ to C₆ alkoxy group, a halogen, or a cyano group.

15. The organic photoelectronic device of claim 14, wherein the p-type light-absorbing material is a compound represented by one of Chemical Formulae 1A-1 to 1B-4:



[Chemical Formula 1A-1]

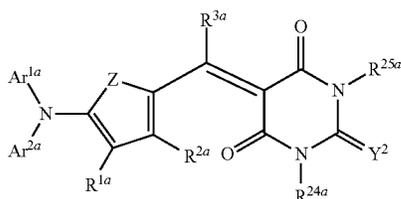


[Chemical Formula 1A-2]

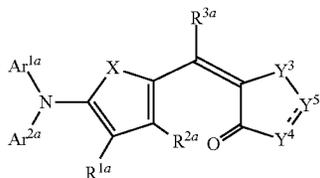
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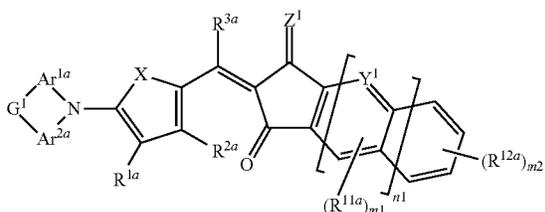
[Chemical Formula 1A-3]



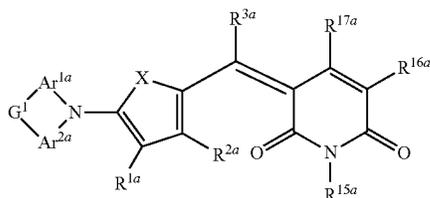
[Chemical Formula 1A-4]



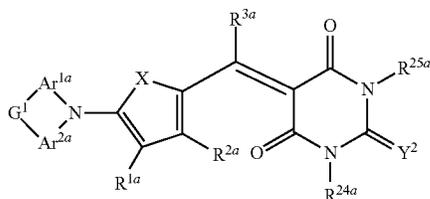
[Chemical Formula 1B-1]



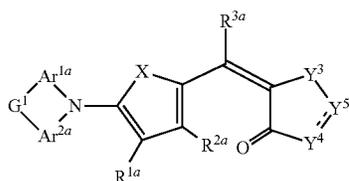
[Chemical Formula 1B-2]



[Chemical Formula 1B-3]



[Chemical Formula 1B-4]



66

wherein, in Chemical Formulae 1A-1 to 1B-4,

X is Se, Te, SO, SO₂, or SiR^aR^b,Z¹ is O or CR^aR^d,Y¹ is N or CR^e,Y² is selected from O, S, Se, Te, and C(R^f)(CN),Y³ is O, S, Se, or Te,Y⁴ is N or NR^{18a},Y⁵ is CR^{19a} or C=CR^{20a}(CN),each of Ar^{1a} and Ar^{2a} are independently a substituted or unsubstituted C₆ to C₃₀ aryl group or a substituted or unsubstituted C₃ to C₃₀ heteroaryl group,G¹ is selected from a single bond, —(CR^gR^h)_{n2}—, —O—, —S—, —Se—, —N—, —NRⁱ—, —SiR^jR^k—, and —GeR^lR^m—, wherein n2 is 1 or 2,each of R^{1a} to R^{3a}, R^{11a}, R^{12a}, R^{15a} to R^{20a}, R^{24a}, R^{25a}, and R^a to R^f are independently hydrogen, a substituted or unsubstituted C₁ to C₃₀ alkyl group, a substituted or unsubstituted C₆ to C₃₀ aryl group, a substituted or unsubstituted C₃ to C₃₀ heteroaryl group, a substituted or unsubstituted C₁ to C₆ alkoxy group, a halogen, or a cyano group,

n1 is 0 or 1,

m1 is 0 or 1, and

m2 is an integer of 0 to 4.

16. An image sensor comprising the organic photoelectronic device of claim 1.

17. An electronic device comprising the image sensor of claim 16.

18. The electronic device of claim 17, wherein the electronic device is a solar cell, an image sensor, a photo-detector, a photo-sensor, and an organic light emitting diode (OLED).

19. An image sensor comprising:

a semiconductor substrate integrated with at least one first photo-sensing device and at least one second photo-sensing device, the first photo-sensing device configured to sense light in one of a first visible light and second visible light wavelength region and the second photo-sensing device configured to sense light in another of the first visible light and second visible light wavelength region; and

at least one third photo-sensing device on the semiconductor substrate, the third photo-sensing device configured to selectively absorb light in a third visible light wavelength region different from the first and second visible light wavelength regions, the third photo-sensing device including the organic photoelectronic device of claim 1.

20. The image sensor of claim 19, wherein the first visible light is in a wavelength region of greater than about 600 nm and less than or equal to about 700 nm,

the second visible light is in a wavelength of greater than or equal to about 400 nm and less than 500 nm, and

the third visible light is in a wavelength of about 500 nm to about 600 nm.

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